

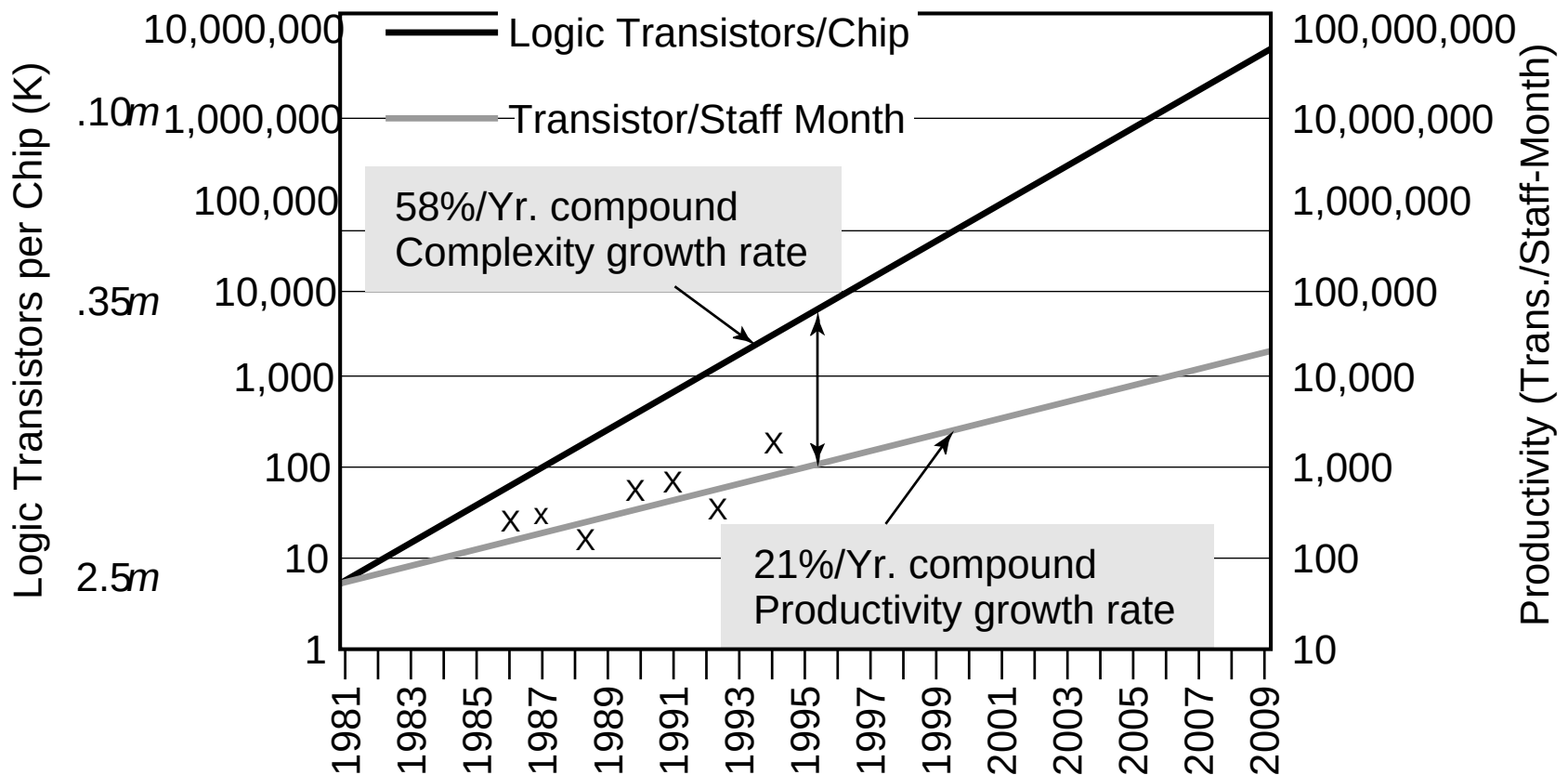


从设计角度透视： 数字集成电路

设计方法学

December 18, 2007

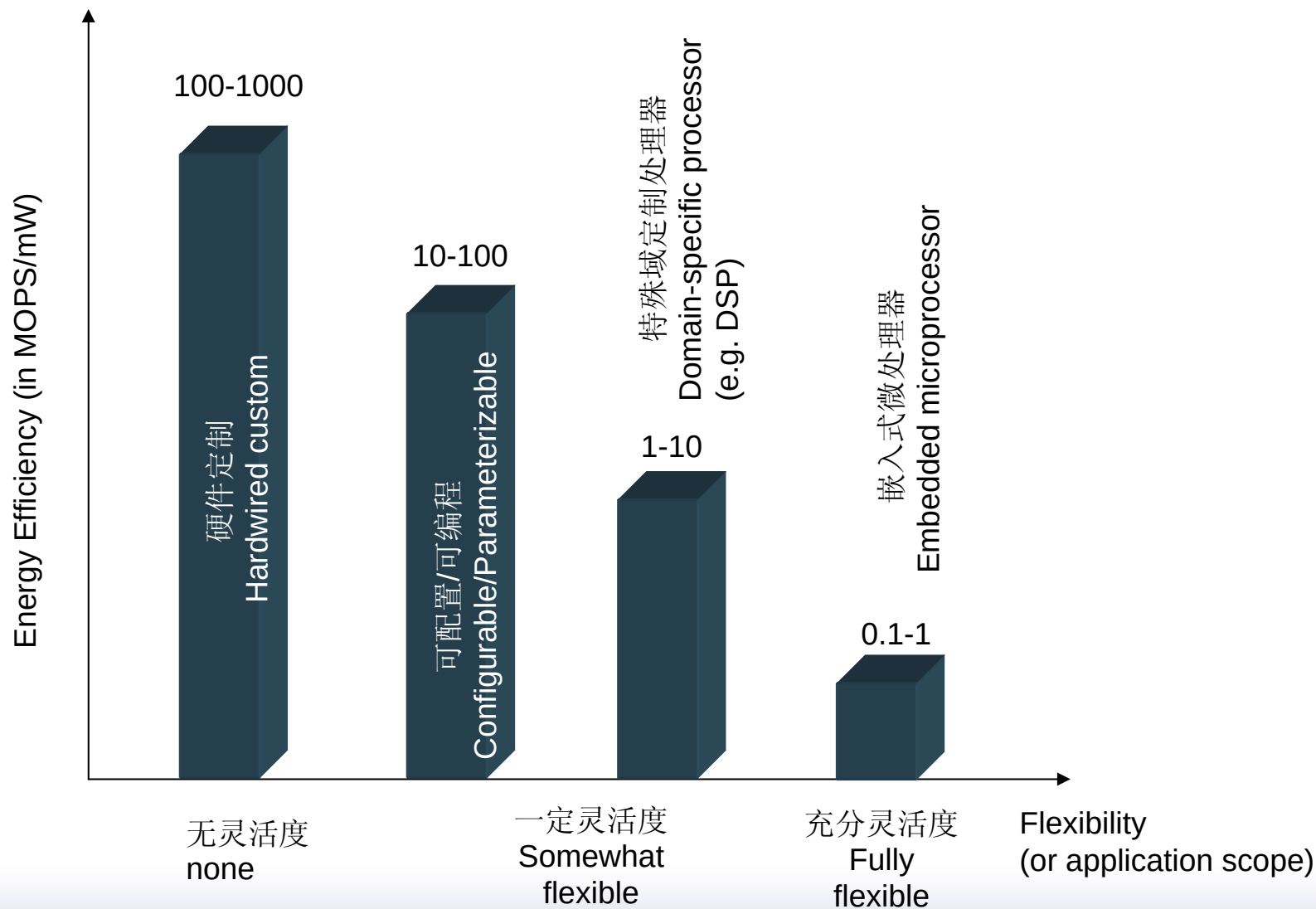
设计生产力的挑战



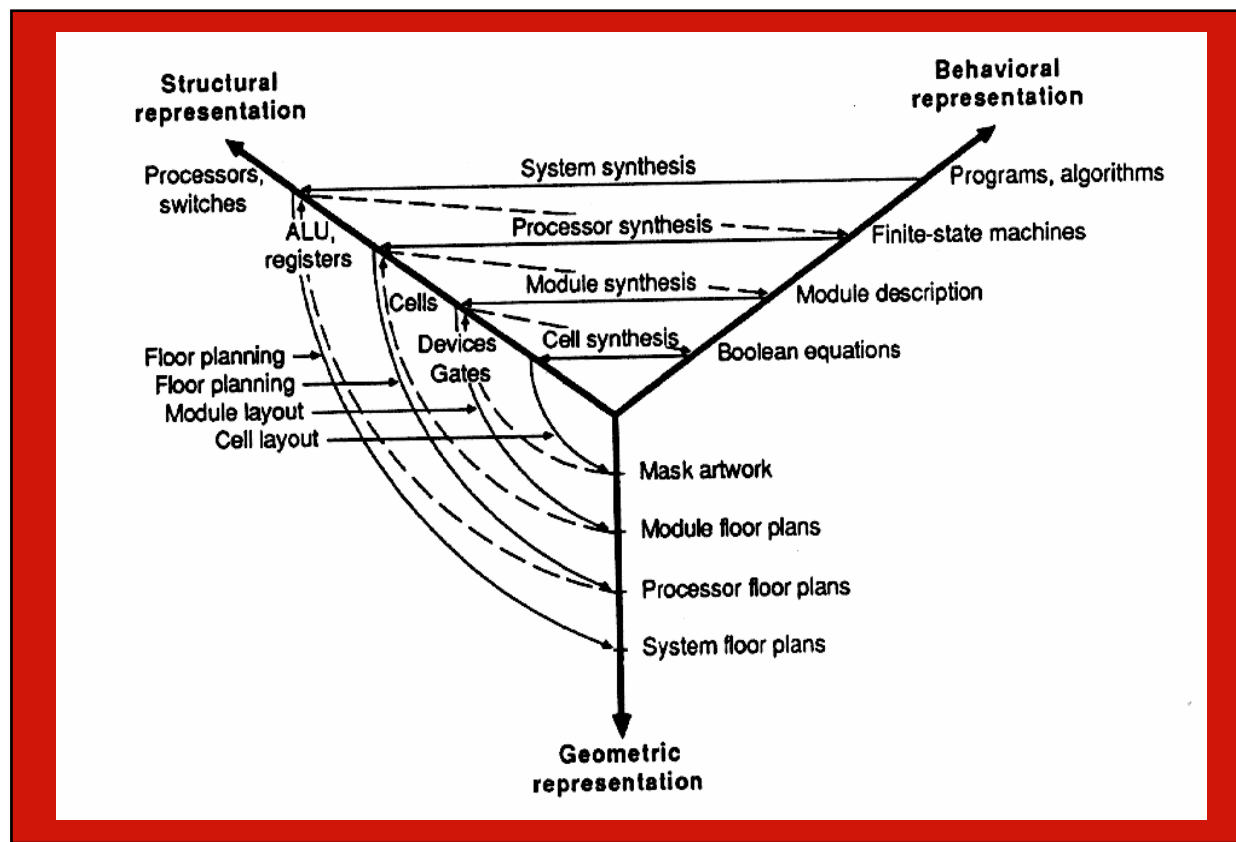
设计复杂度和设计生产力之间日益扩大的差距

Source: sematech97

多种可选的实现方式的冲击

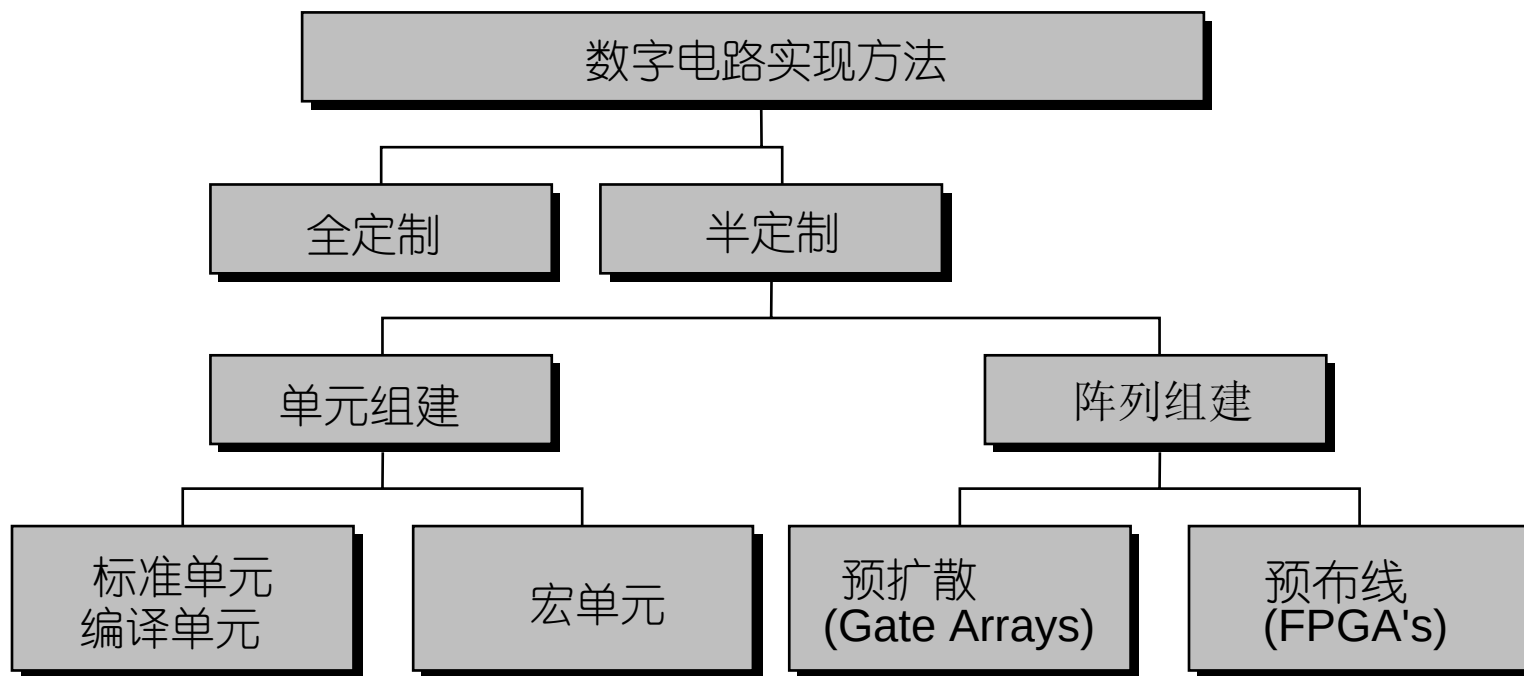


设计方法论

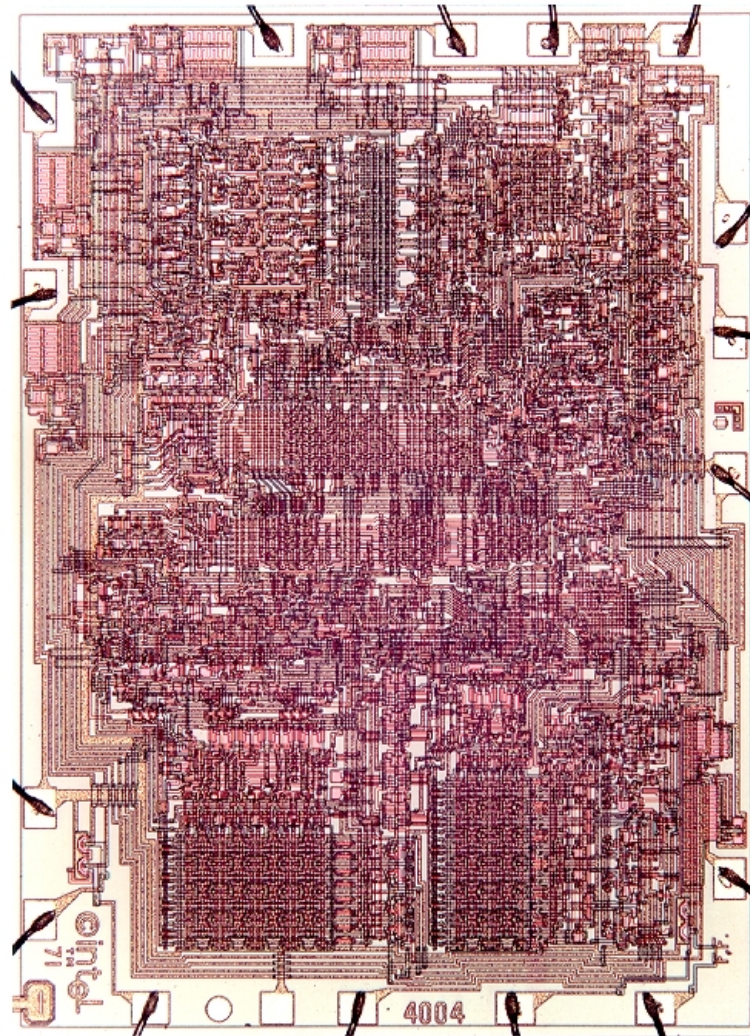


- 关于设计步骤有三种相互交叠的分类表述：行为，结构，和几何
Design process traverses iteratively between three abstractions: behavior, structure, and geometry
- 每一步都愈趋自动化
More and more automation for each of these steps

实现方式选择项

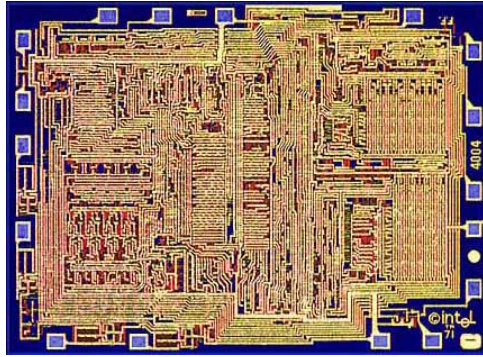


全定制方式

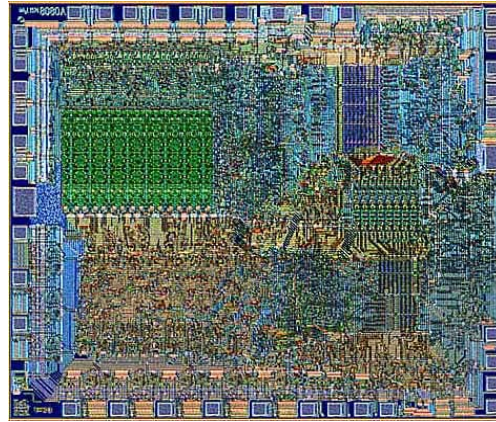


Intel 4004

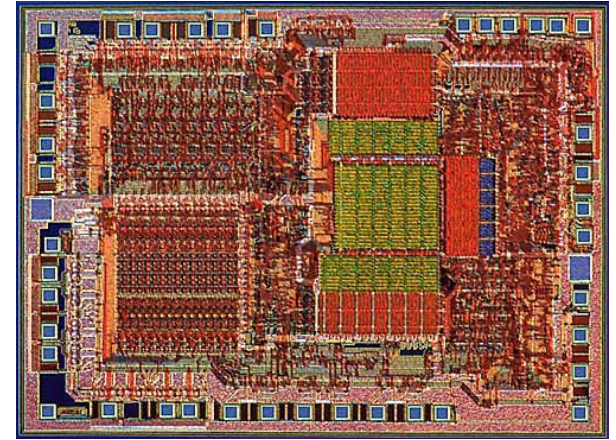
自动化和规整化的转变



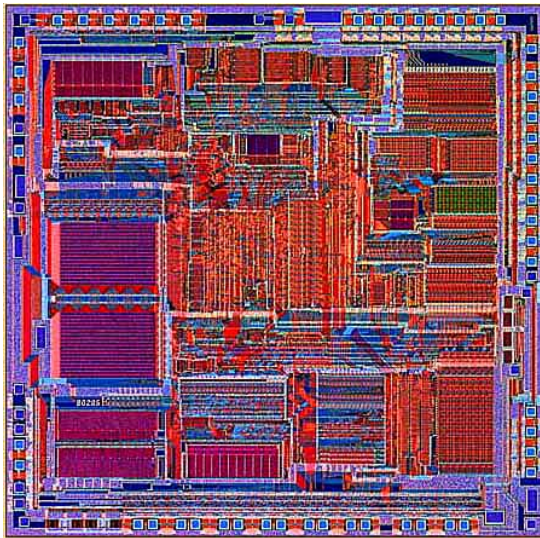
Intel 4004 ('71)



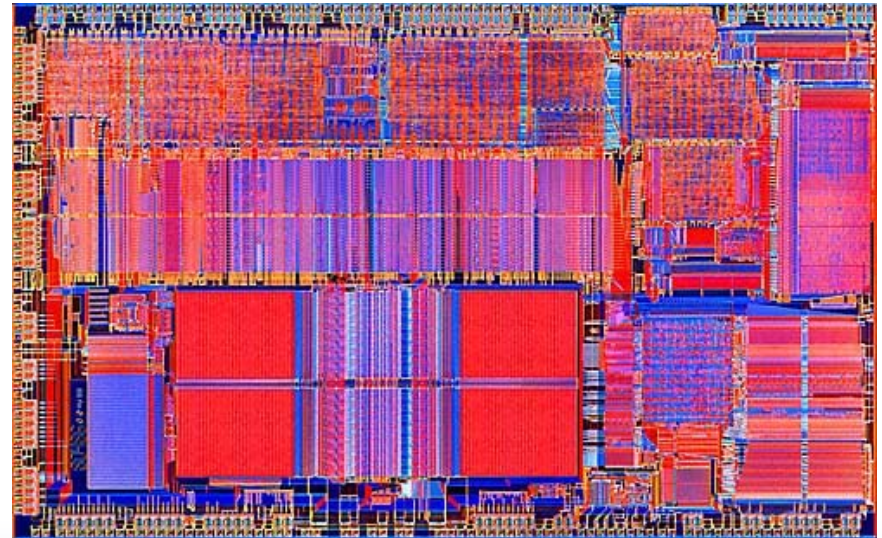
Intel 8080



Intel 8085

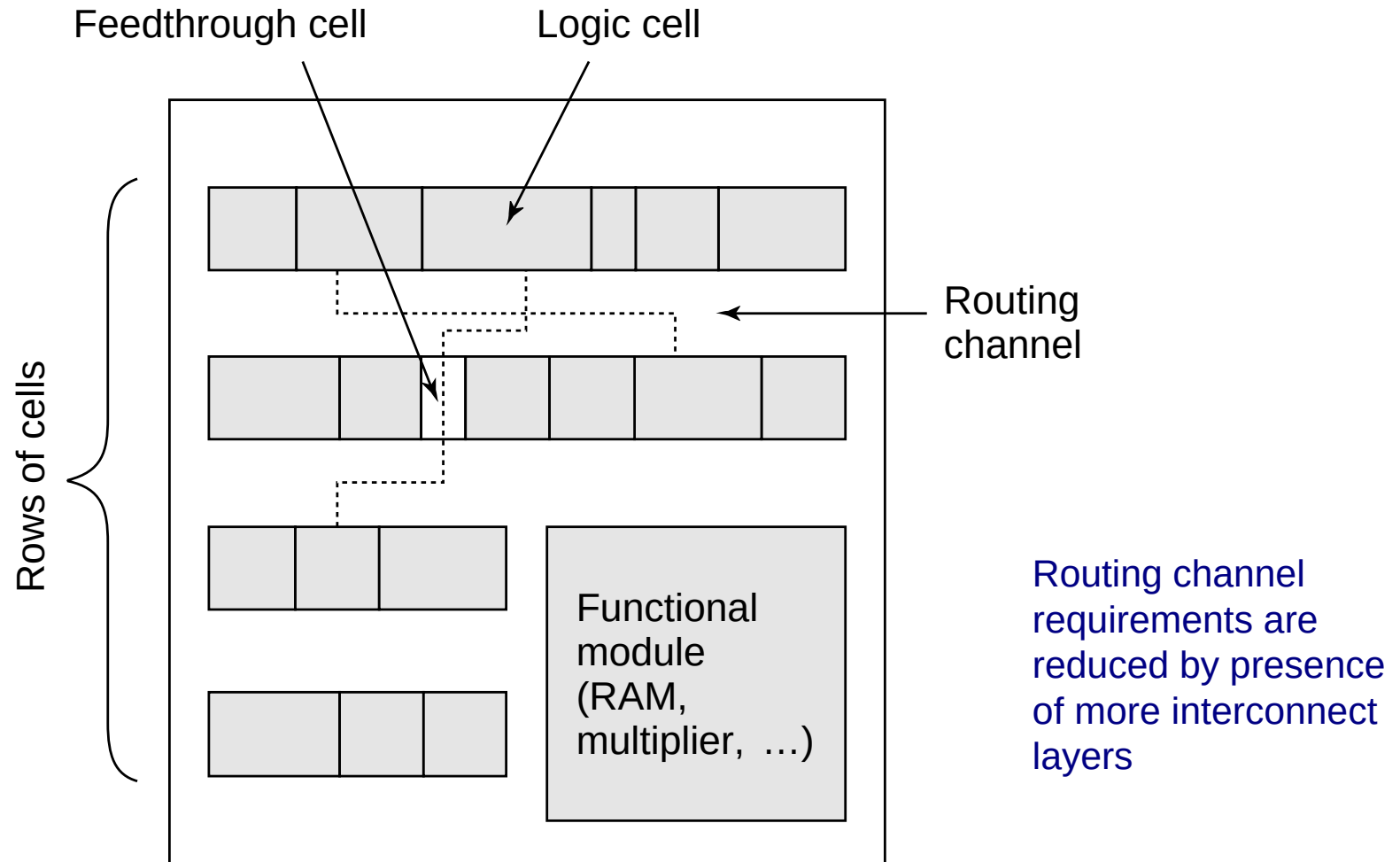


Intel 8286

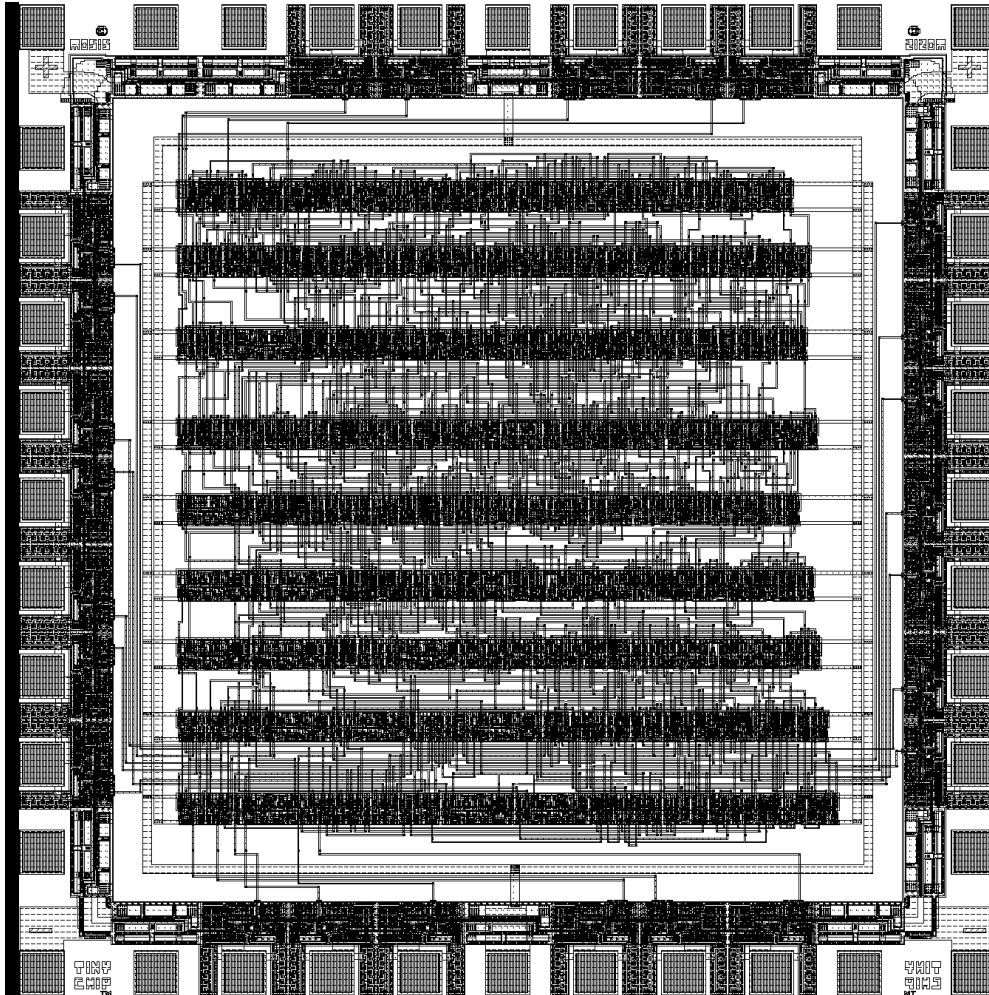


Intel 8486

Cell-based Design (or standard cells)

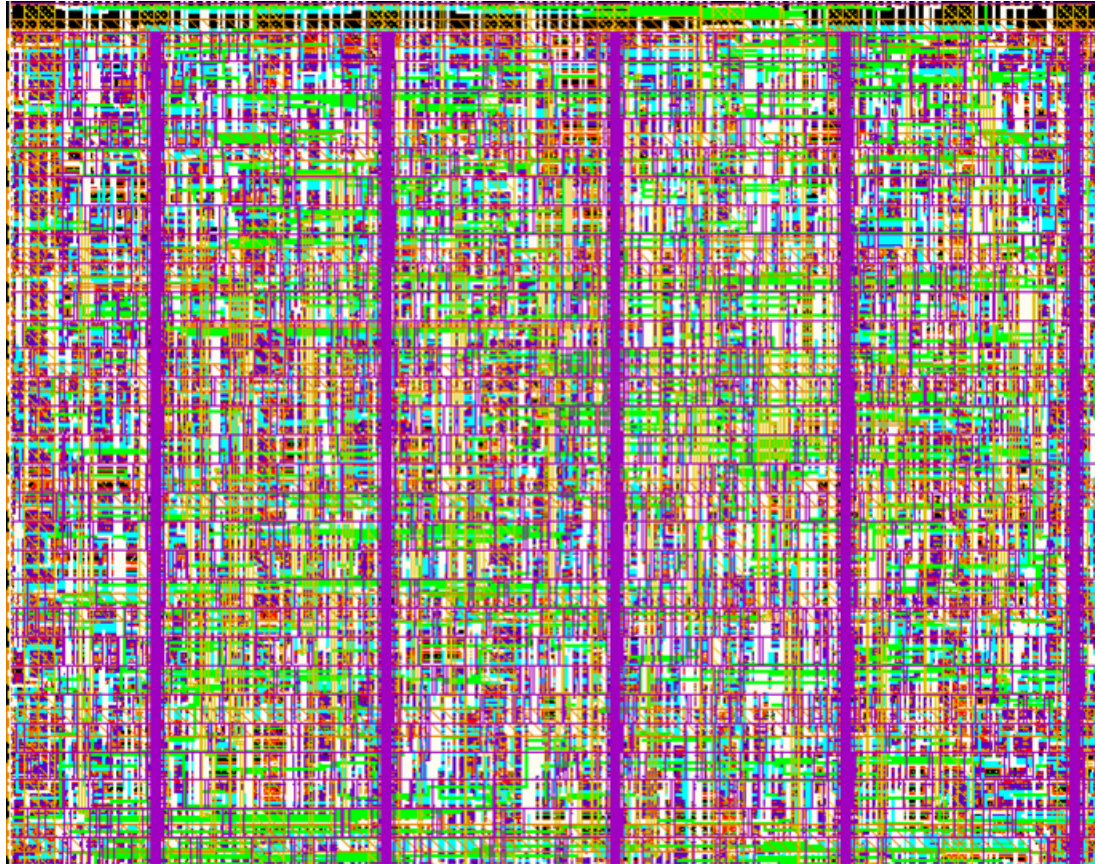


Standard Cell — Example



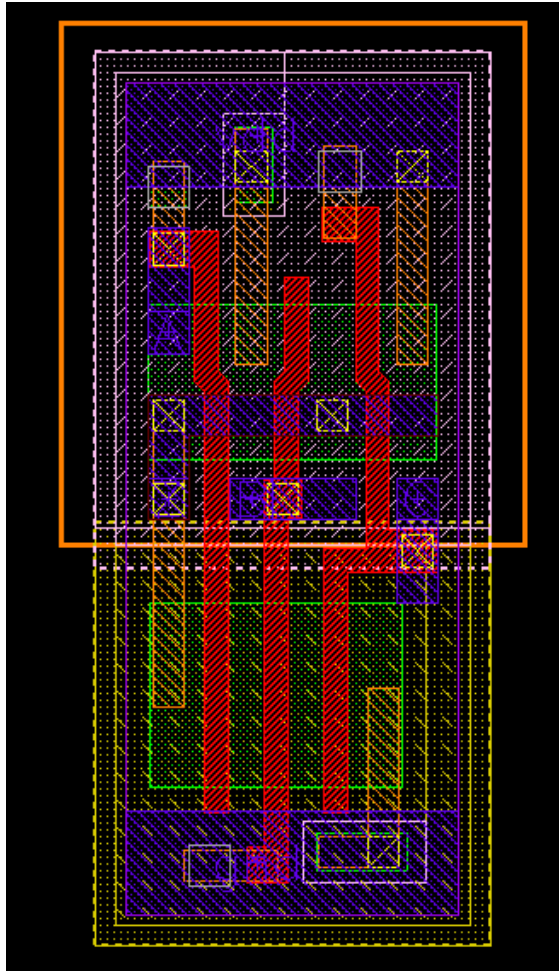
[Brodersen92]

Standard Cell – The New Generation



*Cell-structure
hidden under
interconnect layers*

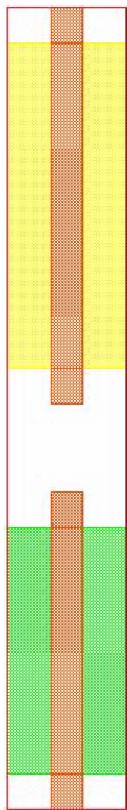
Standard Cell - Example



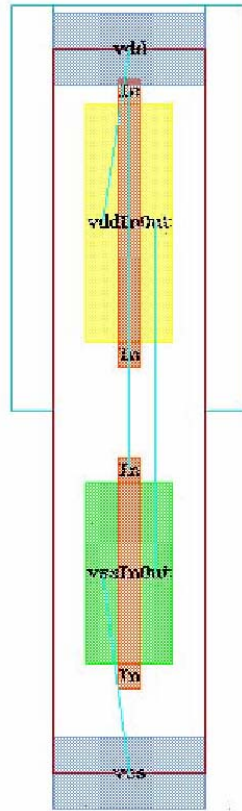
Path	1.2V - 125°C	1.6V - 40°C
$In1-t_{pLH}$	$0.073+7.98C+0.317T$	$0.020+2.73C+0.253T$
$In1-t_{pHL}$	$0.069+8.43C+0.364T$	$0.018+2.14C+0.292T$
$In2-t_{pLH}$	$0.101+7.97C+0.318T$	$0.026+2.38C+0.255T$
$In2-t_{pHL}$	$0.097+8.42C+0.325T$	$0.023+2.14C+0.269T$
$In3-t_{pLH}$	$0.120+8.00C+0.318T$	$0.031+2.37C+0.258T$
$In3-t_{pHL}$	$0.110+8.41C+0.280T$	$0.027+2.15C+0.223T$

3-input NAND cell
(from ST Microelectronics):
C = Load capacitance
T = input rise/fall time

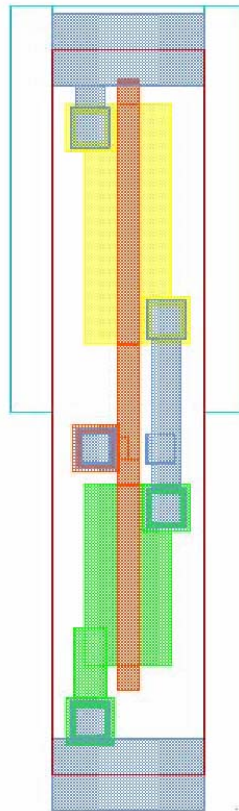
单元自动生成过程



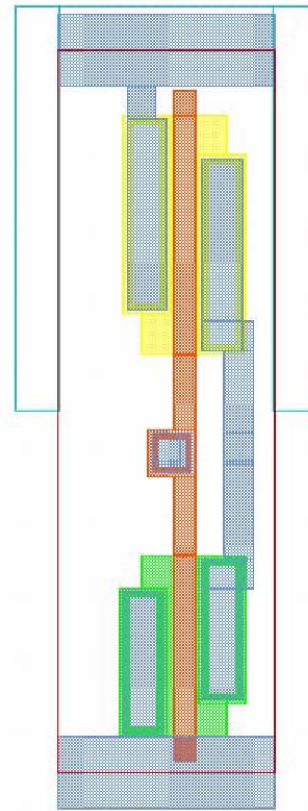
Initial transistor geometries



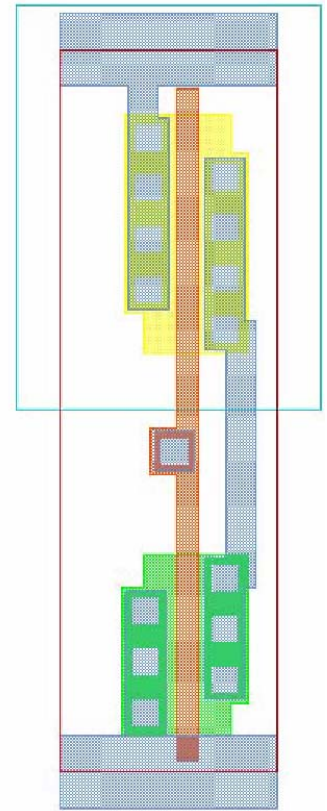
Placed transistors



Routed cell

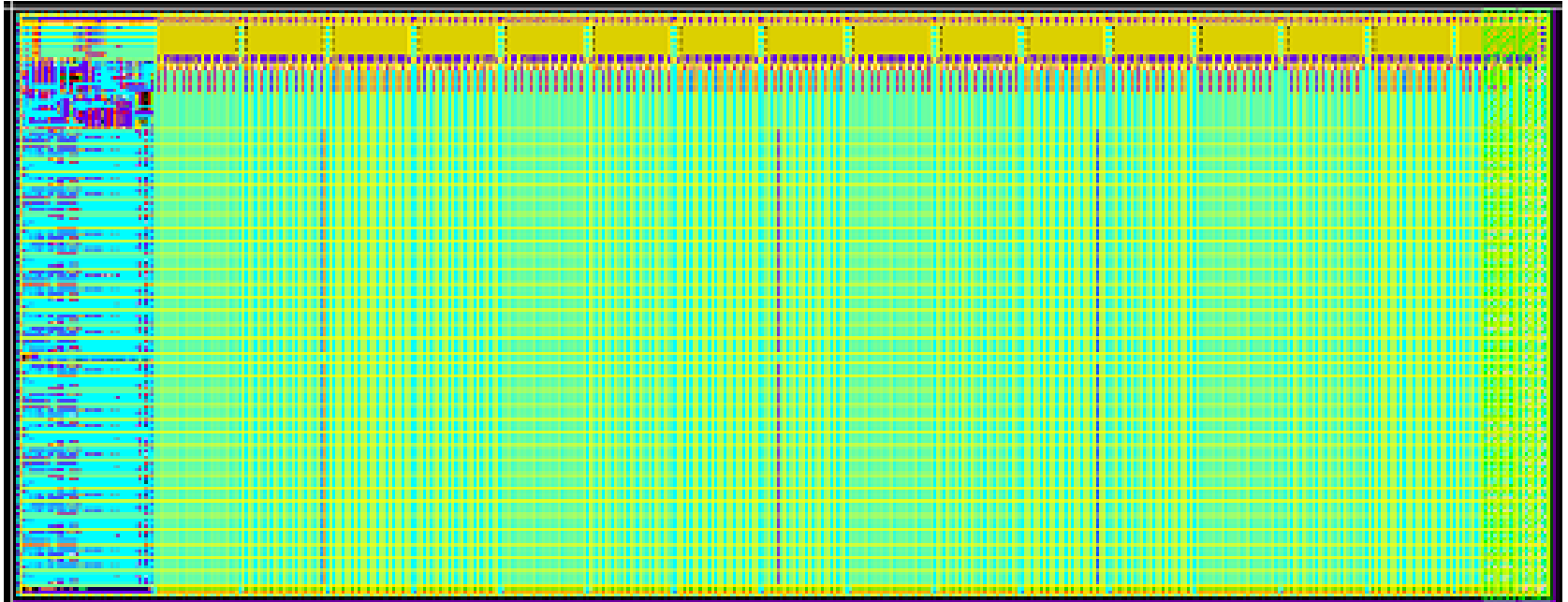


Compacted cell



Finished cell

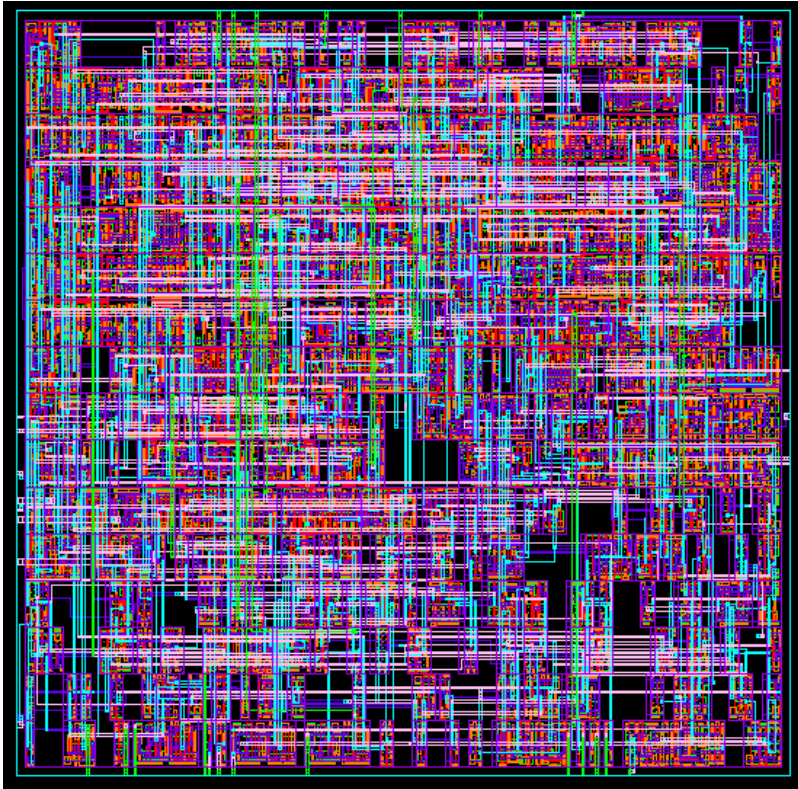
宏模块



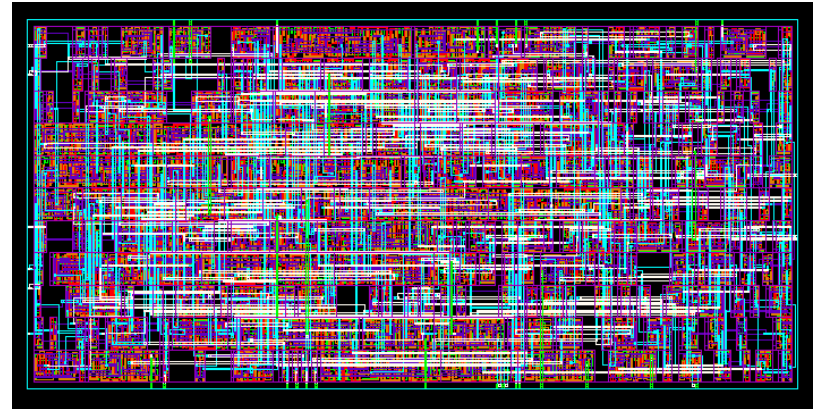
256×32 (or 8192 bit) SRAM

Generated by hard-macro module generator

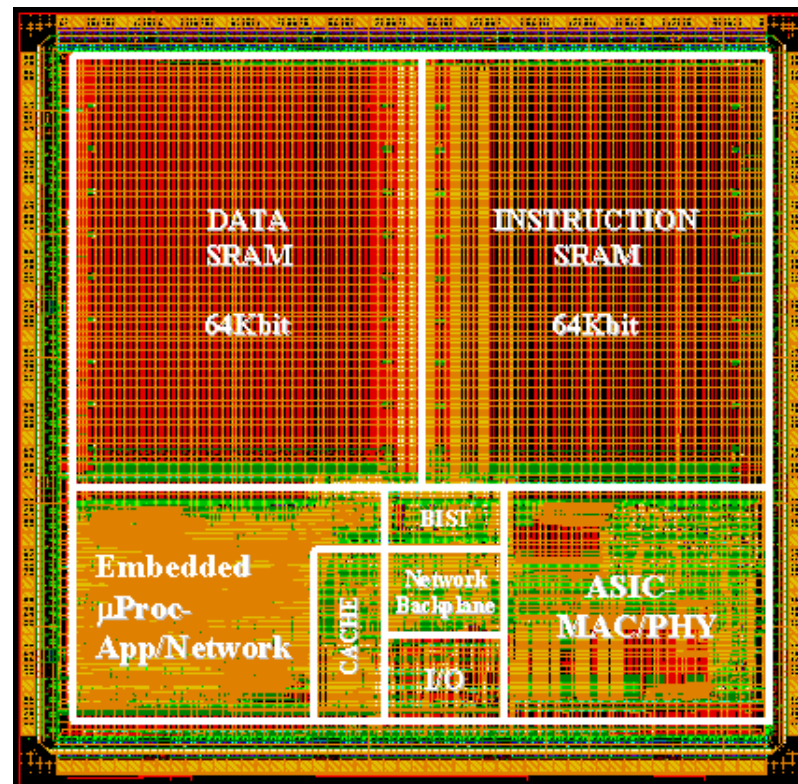
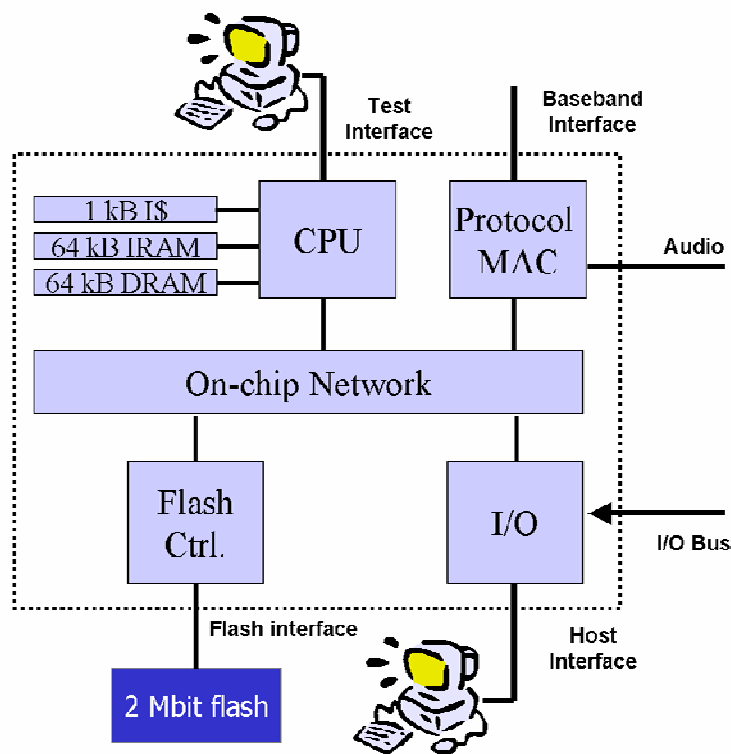
软宏模块



```
string mat = "booth";  
directive (multtype = mat);  
output signed [16] Z = A * B;
```

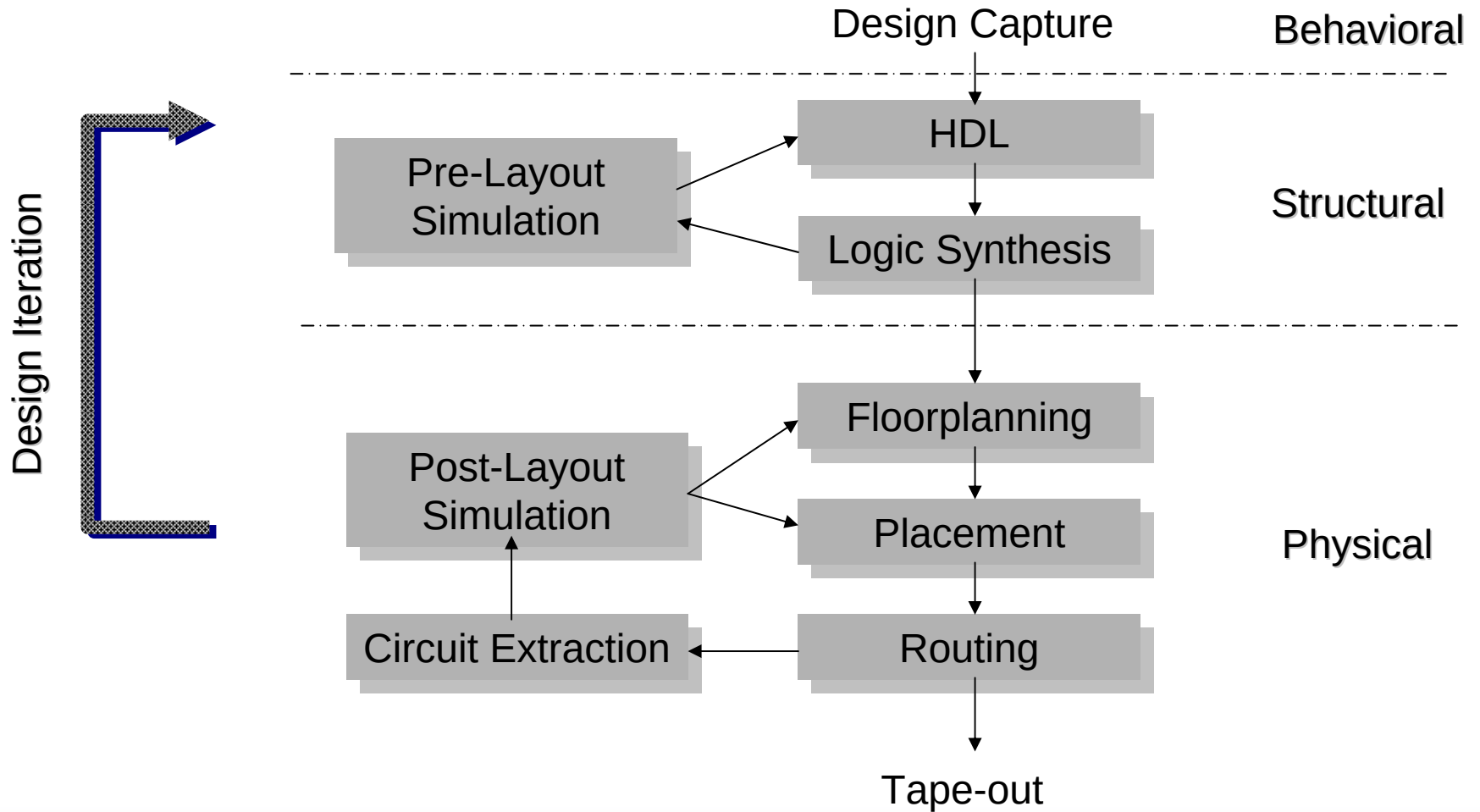


知识产权“Intellectual Property”

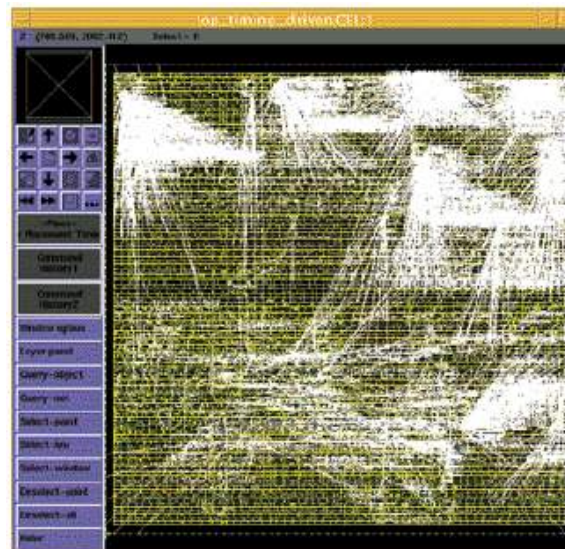


一个应用于无线协议的处理器

半定制流程



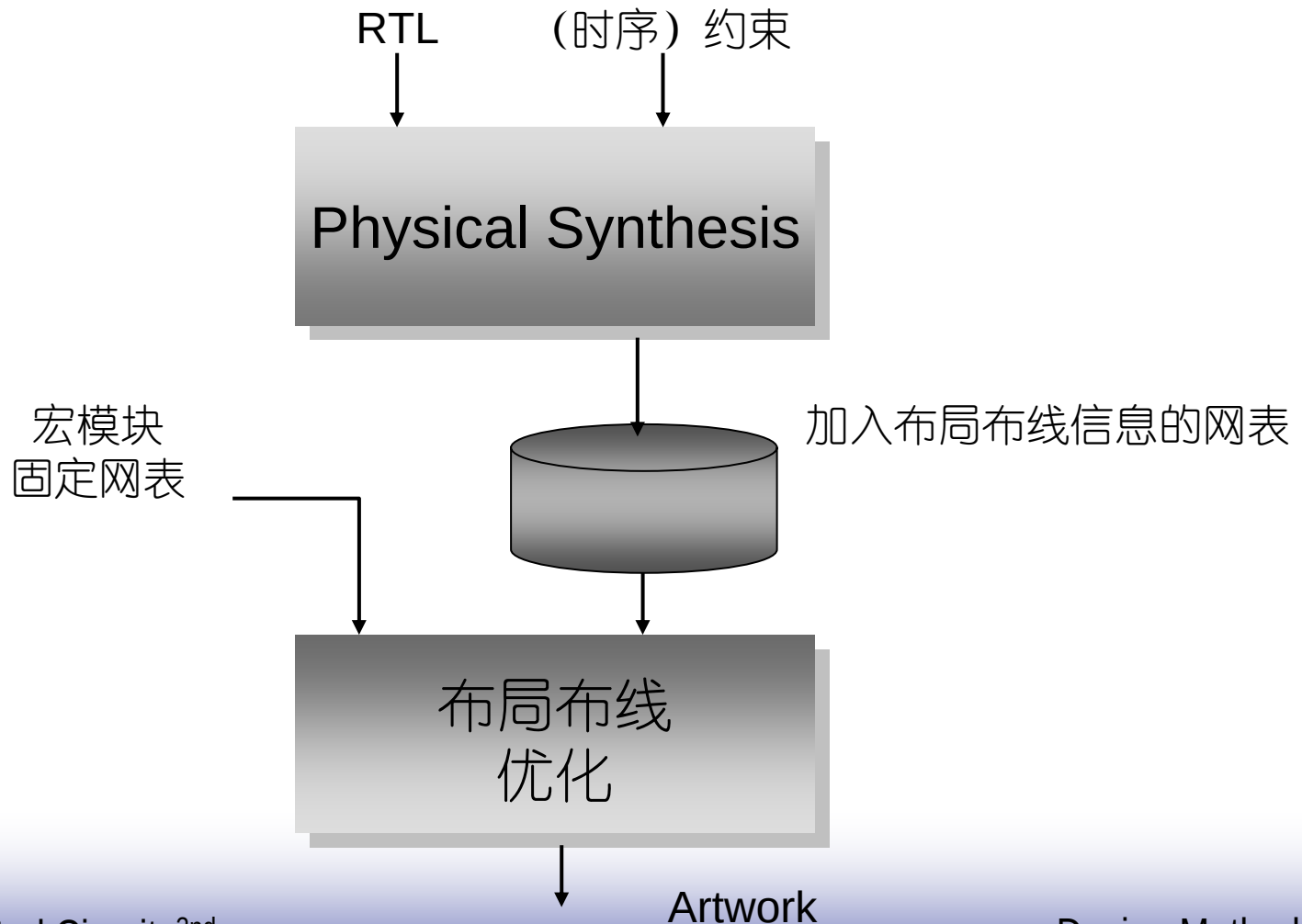
设计收敛问题



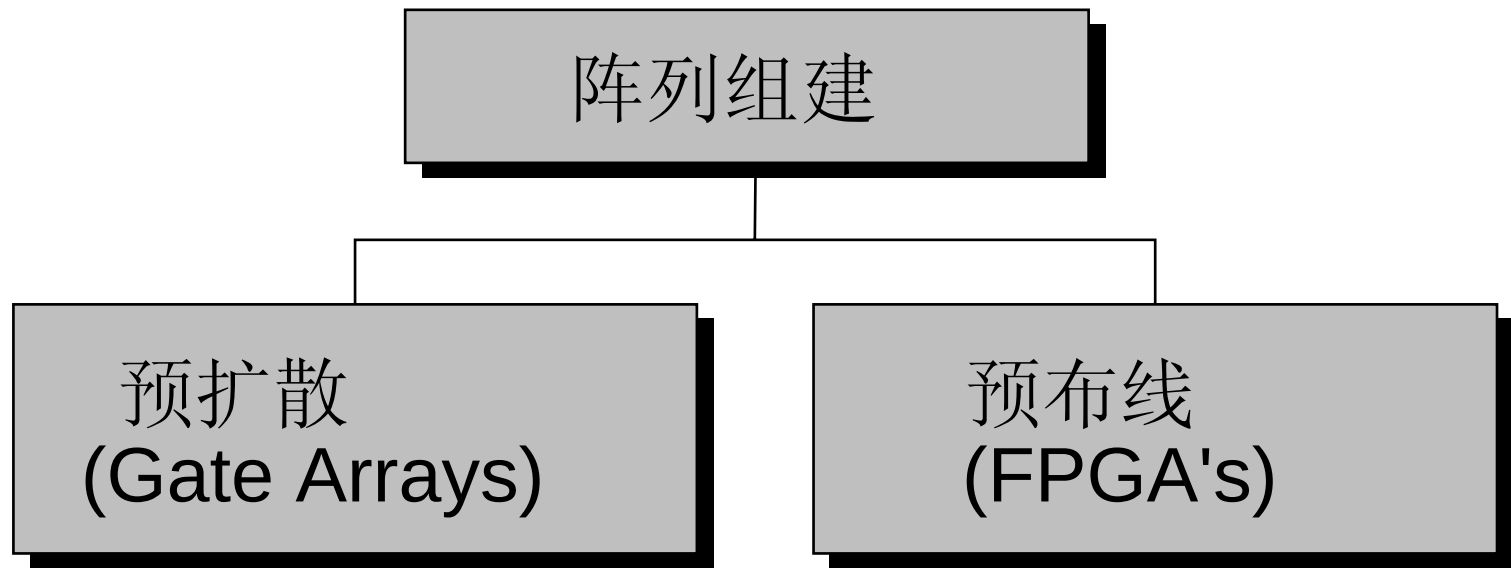
时序误差的迭代消除 (白线)

Iterative Removal of Timing Violations (white lines)

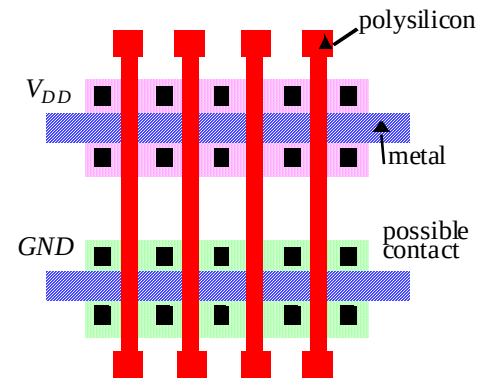
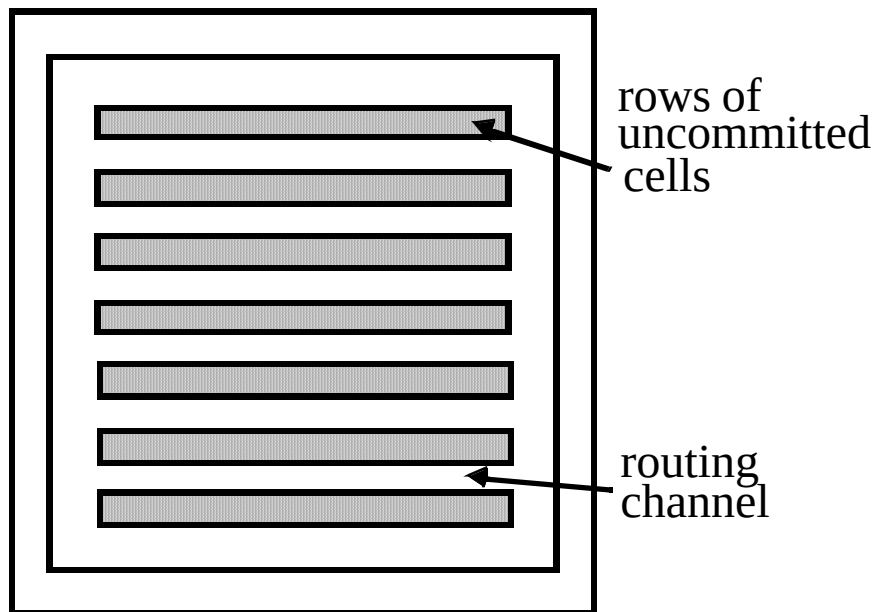
物理设计的整合综合



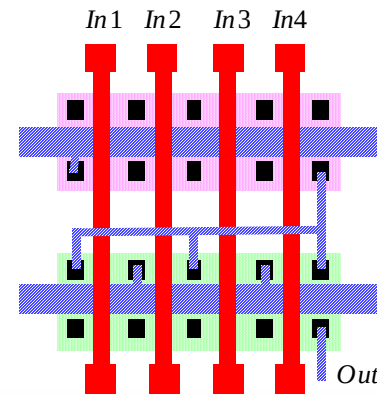
后绑定实现方法



门阵列—Sea-of-gates

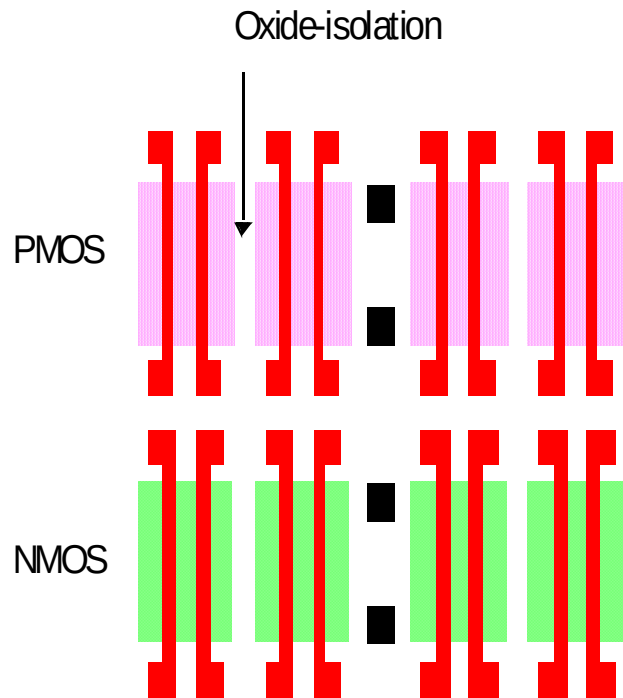


未成形单元

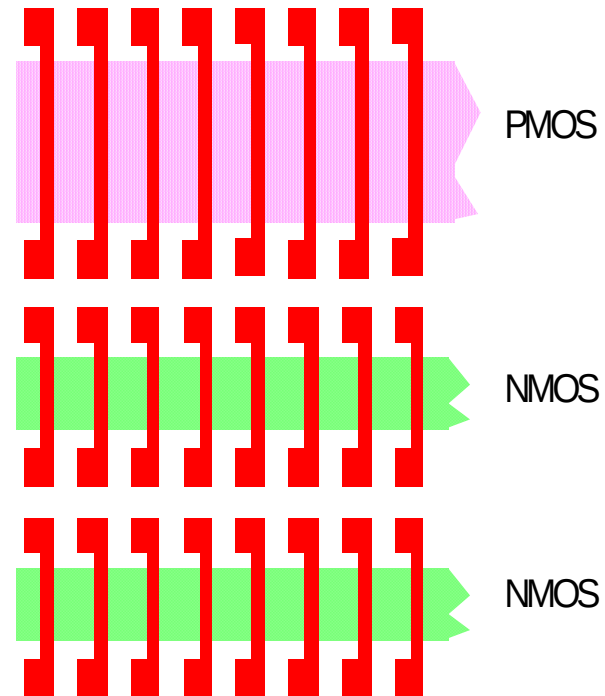


成形单元
(4-input NOR)

门阵列原始单元

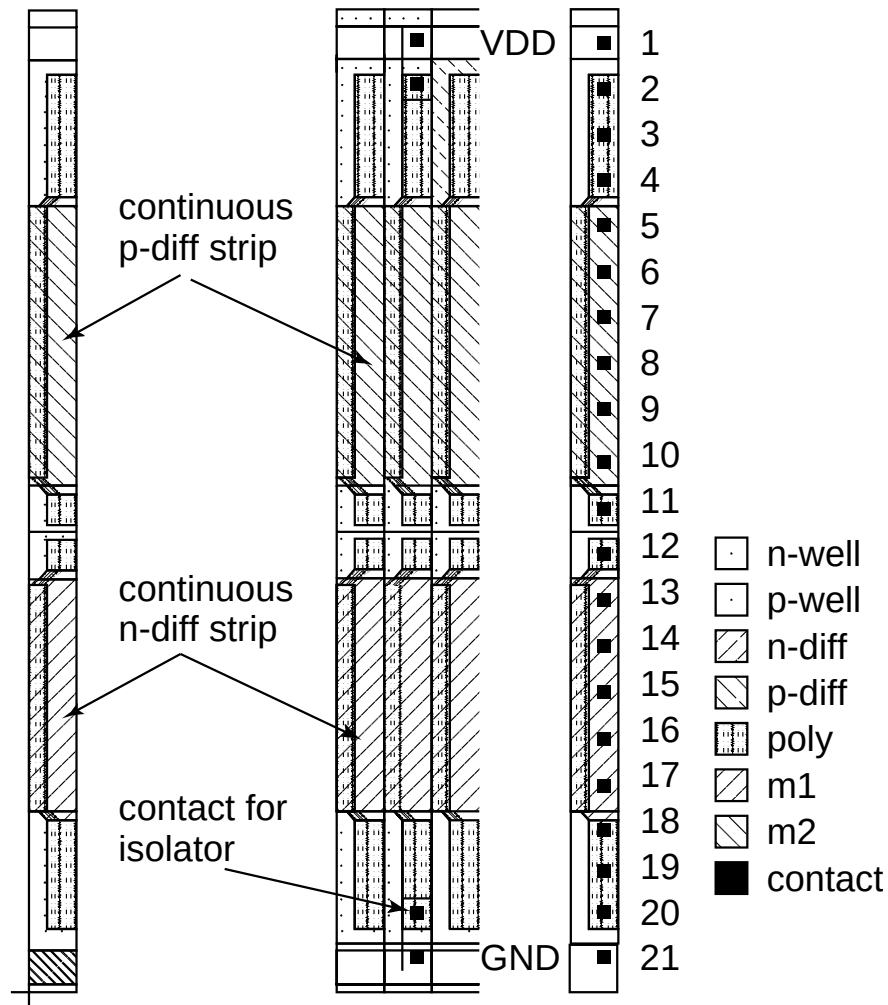


氧化物隔离

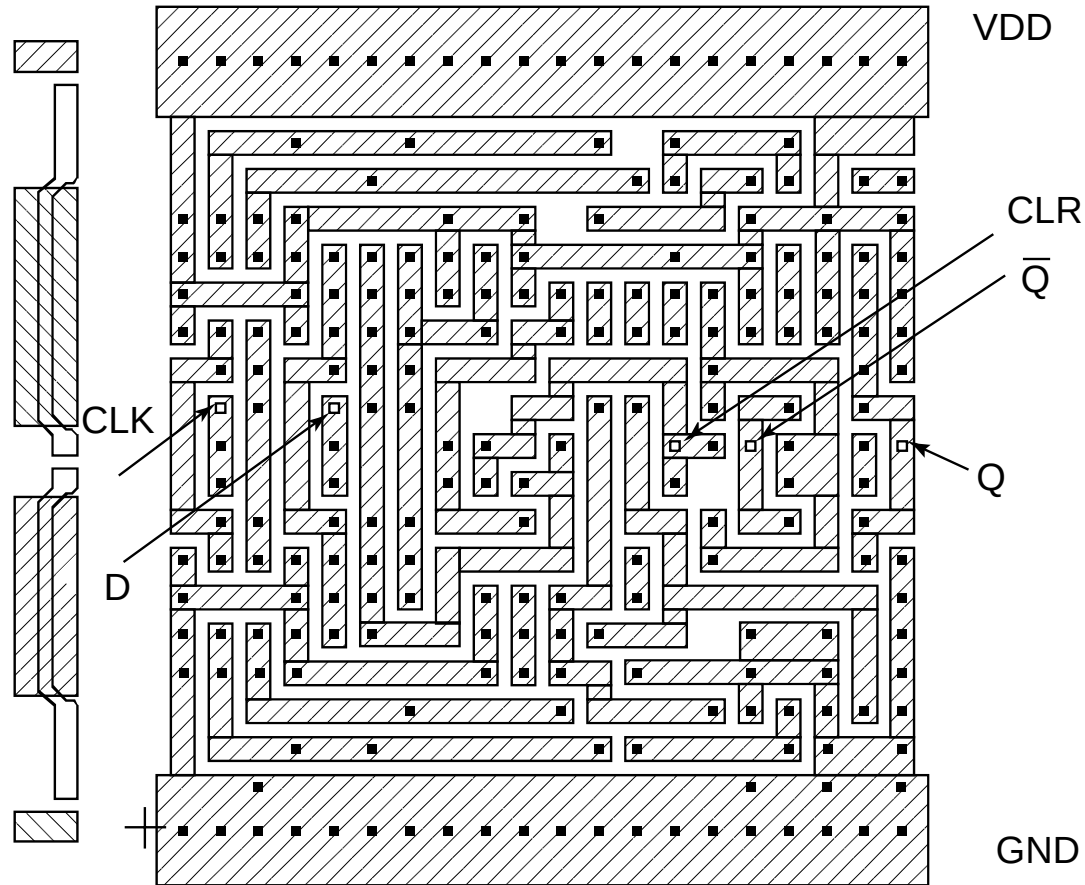


门隔离

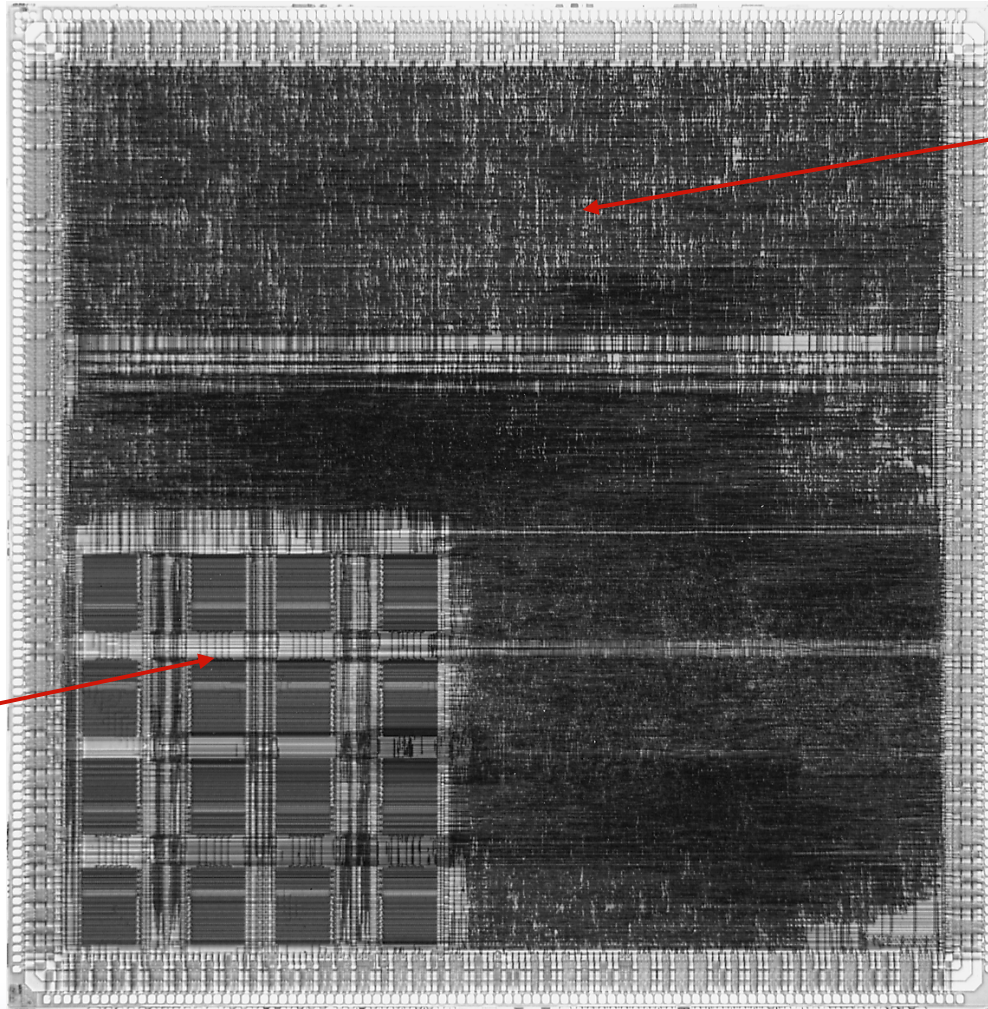
举例: 门隔离门阵列的基本单元



举例: 门隔离门阵列的寄存器单元



门阵列 (门海)



Random Logic

Memory
Subsystem

LSI Logic LEA300K
(0.6 μm CMOS)

预布线阵列

预布线阵列(可编程器件)分类:

□ 根据编程技术

- 熔丝阵列 (编程一次)
- 不挥发性EPROM阵列
- RAM阵列

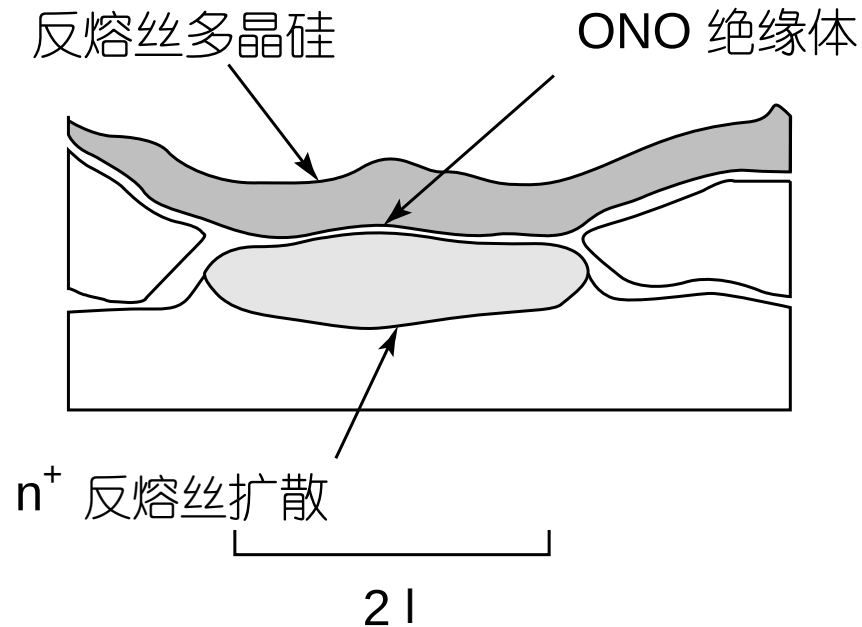
□ 可编程的逻辑风格

- 阵列方式
- 查找表方式

□ 可编程的内联风格

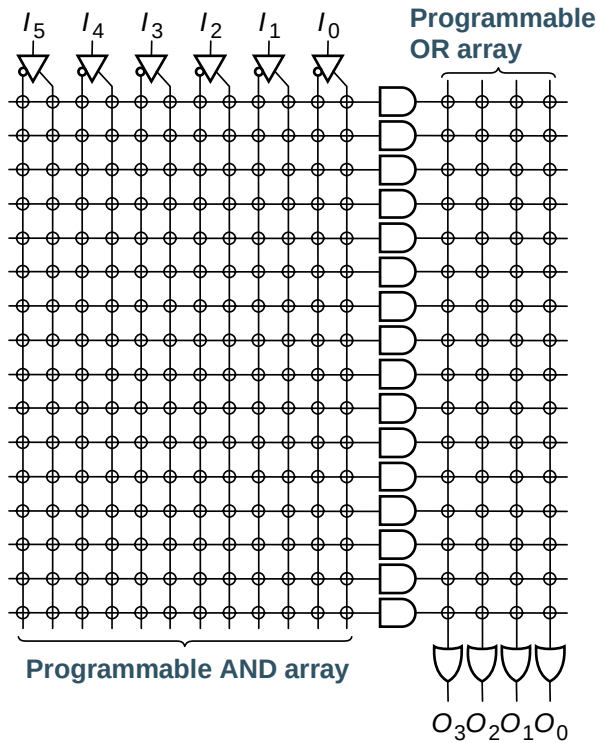
- 道式布线
- 网状互联

基于熔丝的FPGA

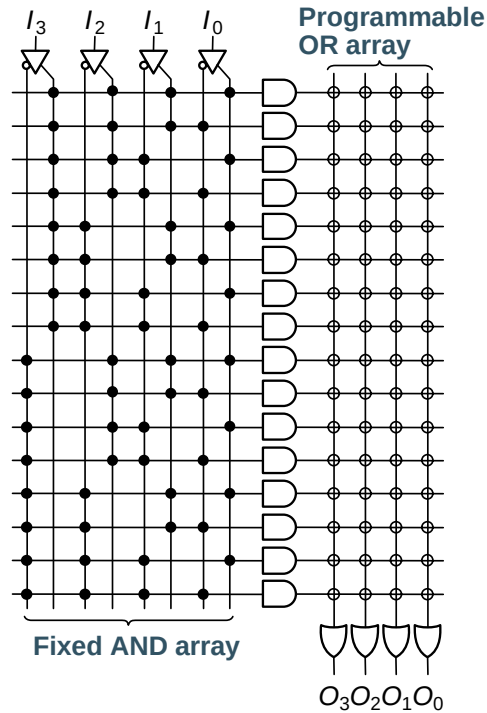


初始为断开状态, 施加脉冲电流后连接

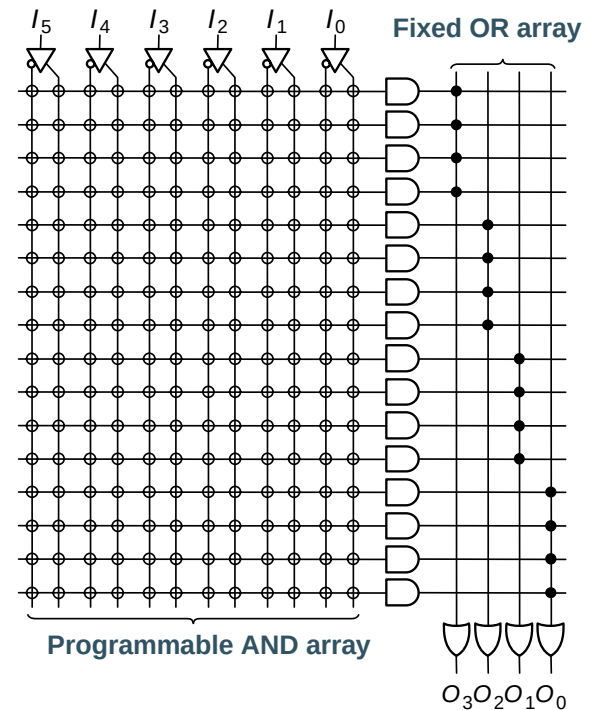
可编程逻辑阵列



PLA



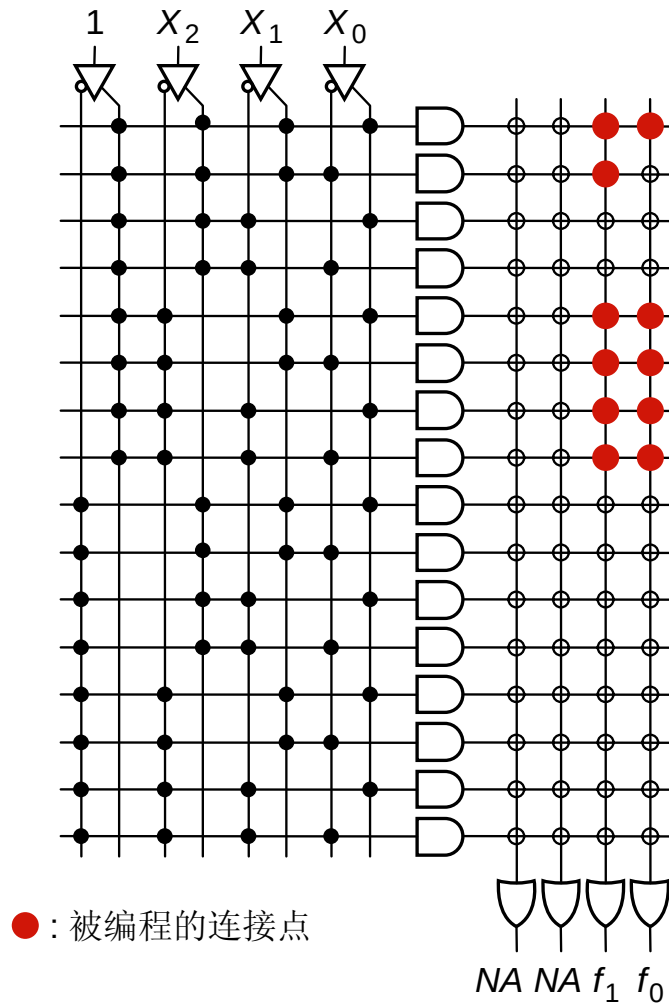
PROM



PAL

⊕ 表可编程连接
 • 表确定连接

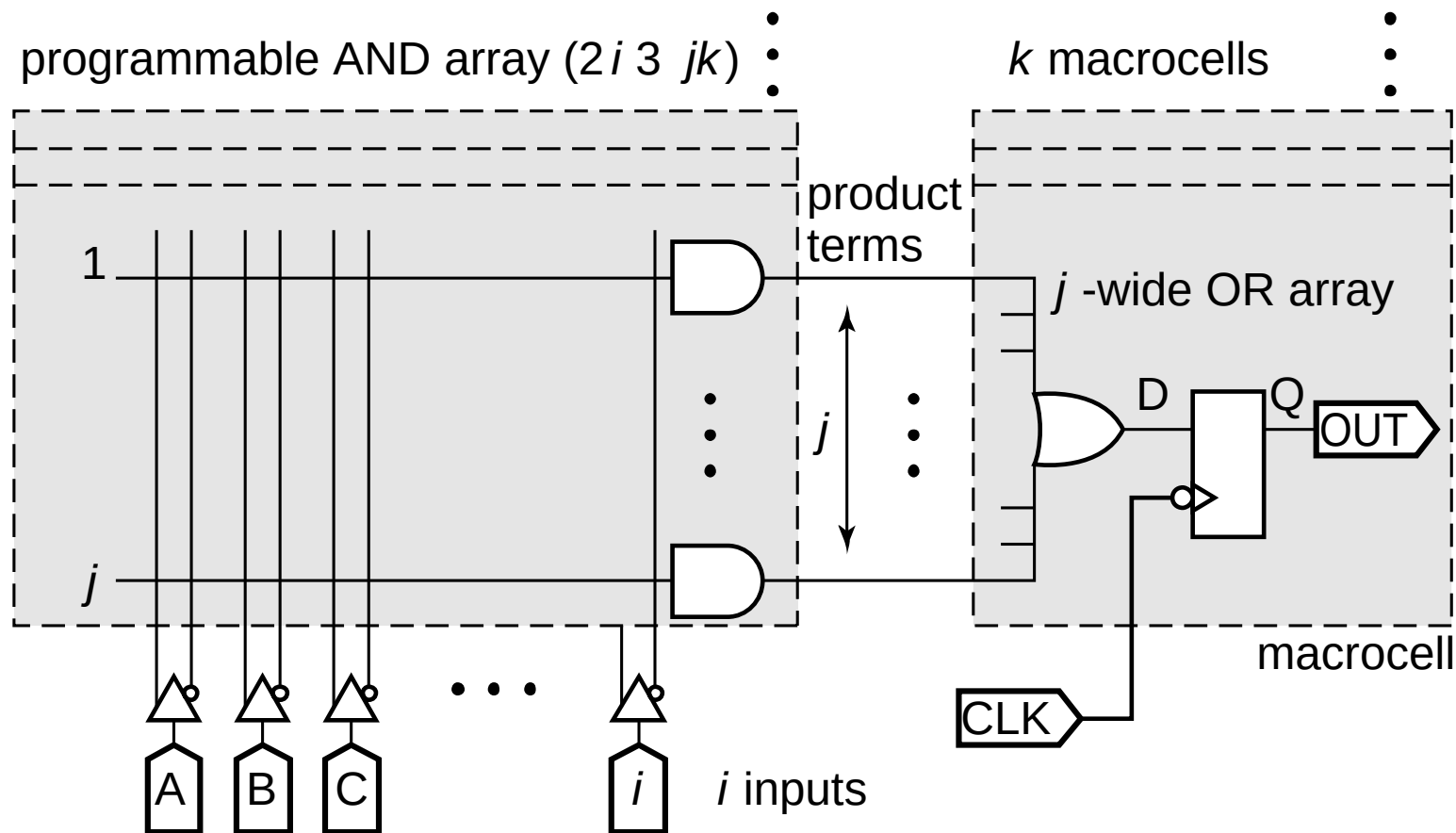
编程一个PROM



$$f_0 = x_0 x_1 + \overline{x_2}$$

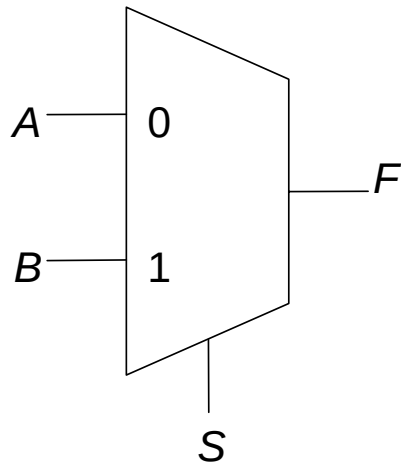
$$f_1 = x_0 x_1 x_2 + \overline{x_2} + \overline{x_0} x_1$$

较复杂的PAL



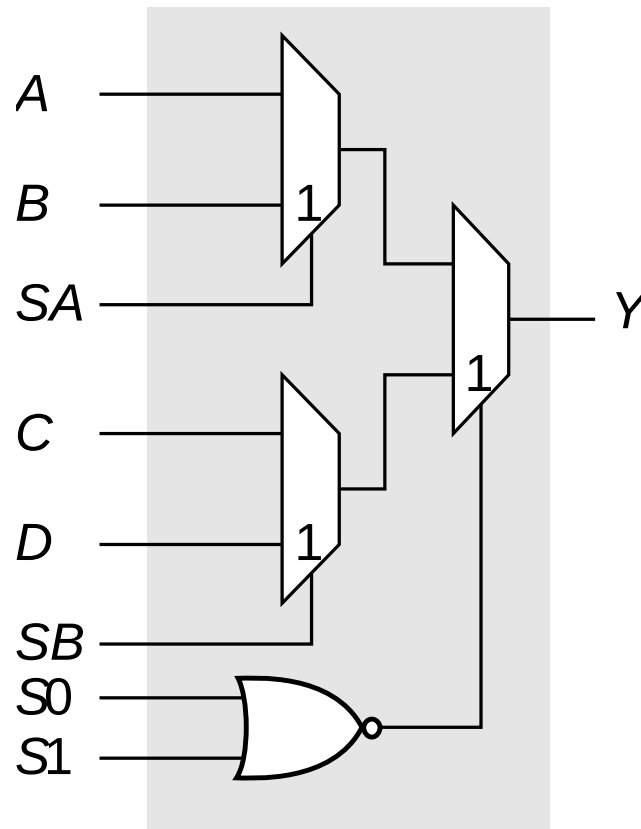
i 表输入, j 表最小项/宏单元, k 表宏单元

作为可编程逻辑的二输入选择器

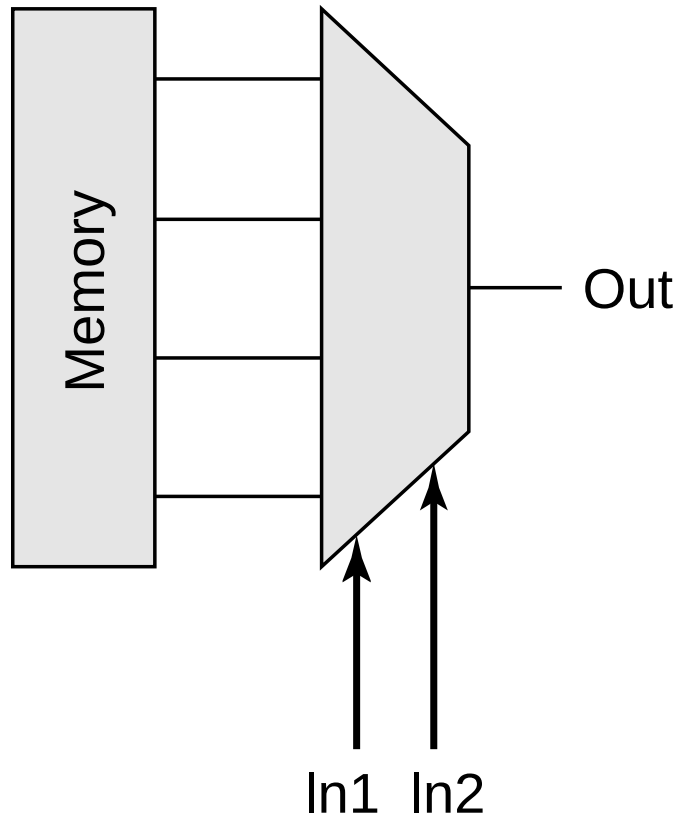


Configuration			F=
A	B	S	
0	0	0	0
0	X	1	X
0	Y	1	Y
0	Y	X	XY
X	0	Y	$X\bar{Y}$
Y	0	X	$\bar{X}Y$
Y	1	X	$X1Y$
1	0	X	$\bar{X}$
1	0	Y	$\bar{Y}$
1	1	1	1

Actel 的熔丝 FPGA 逻辑单元



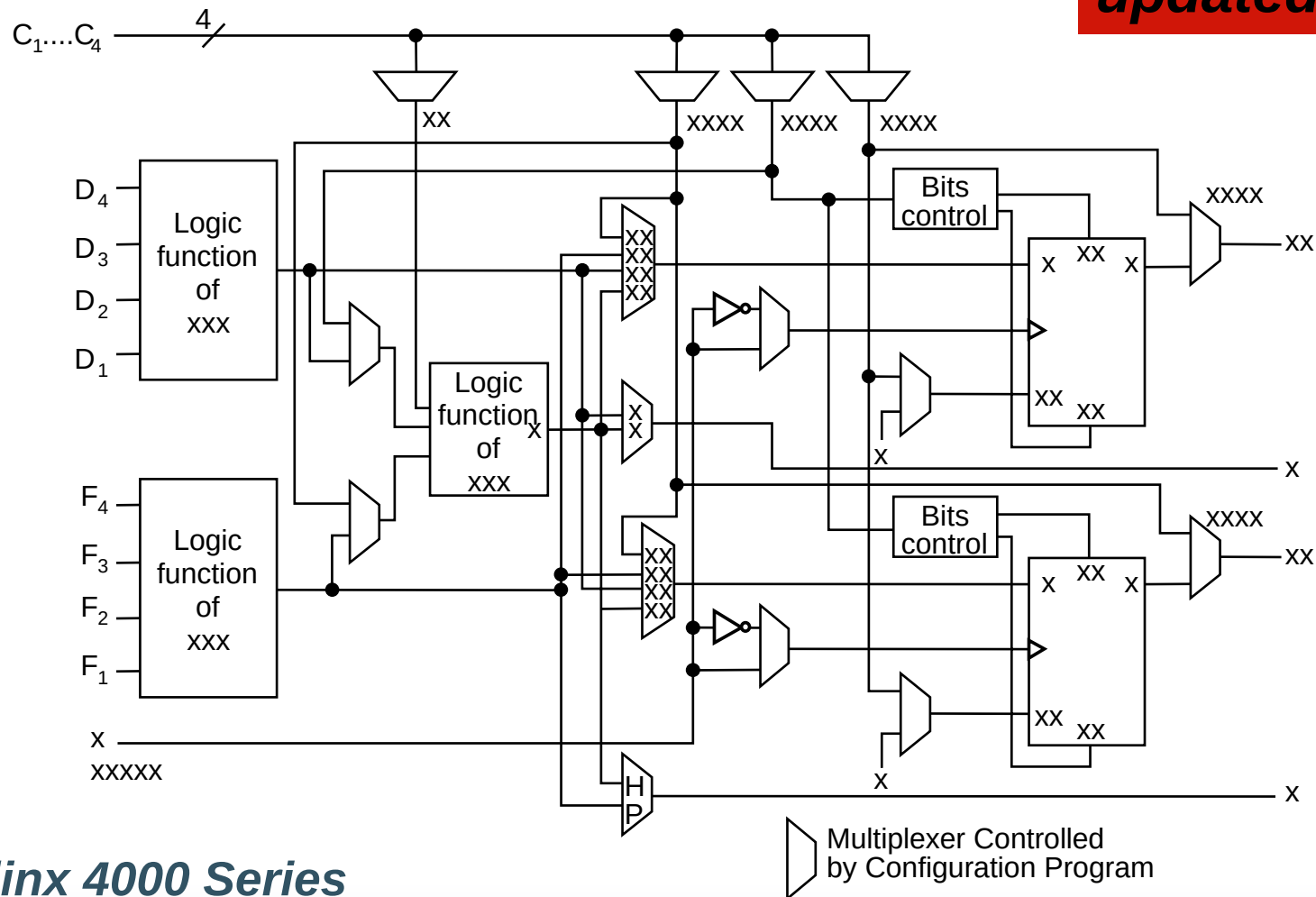
查找表的逻辑单元



In	Out
00	00
01	1
10	1
11	0

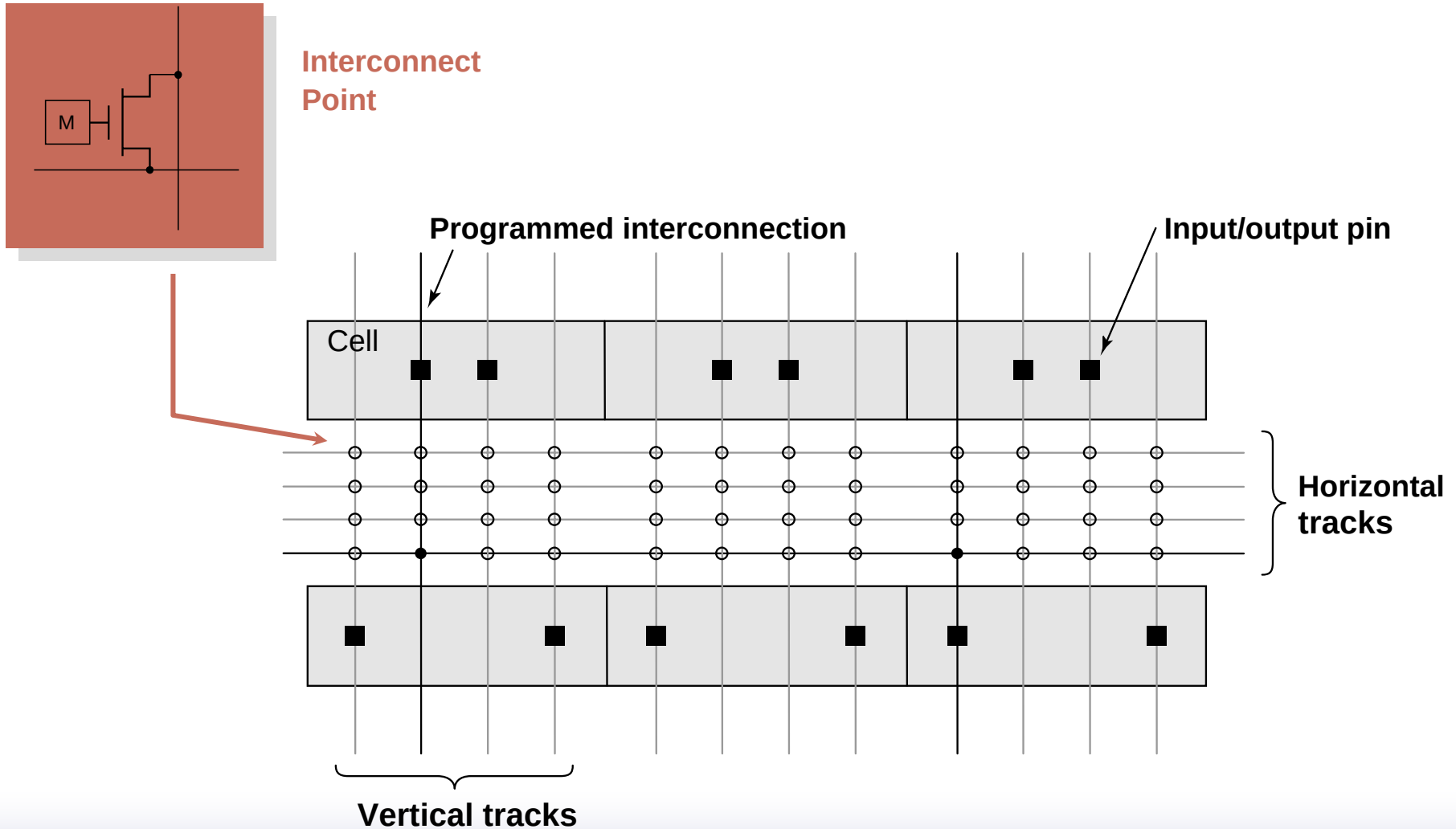
查找表逻辑单元

Figure must be updated

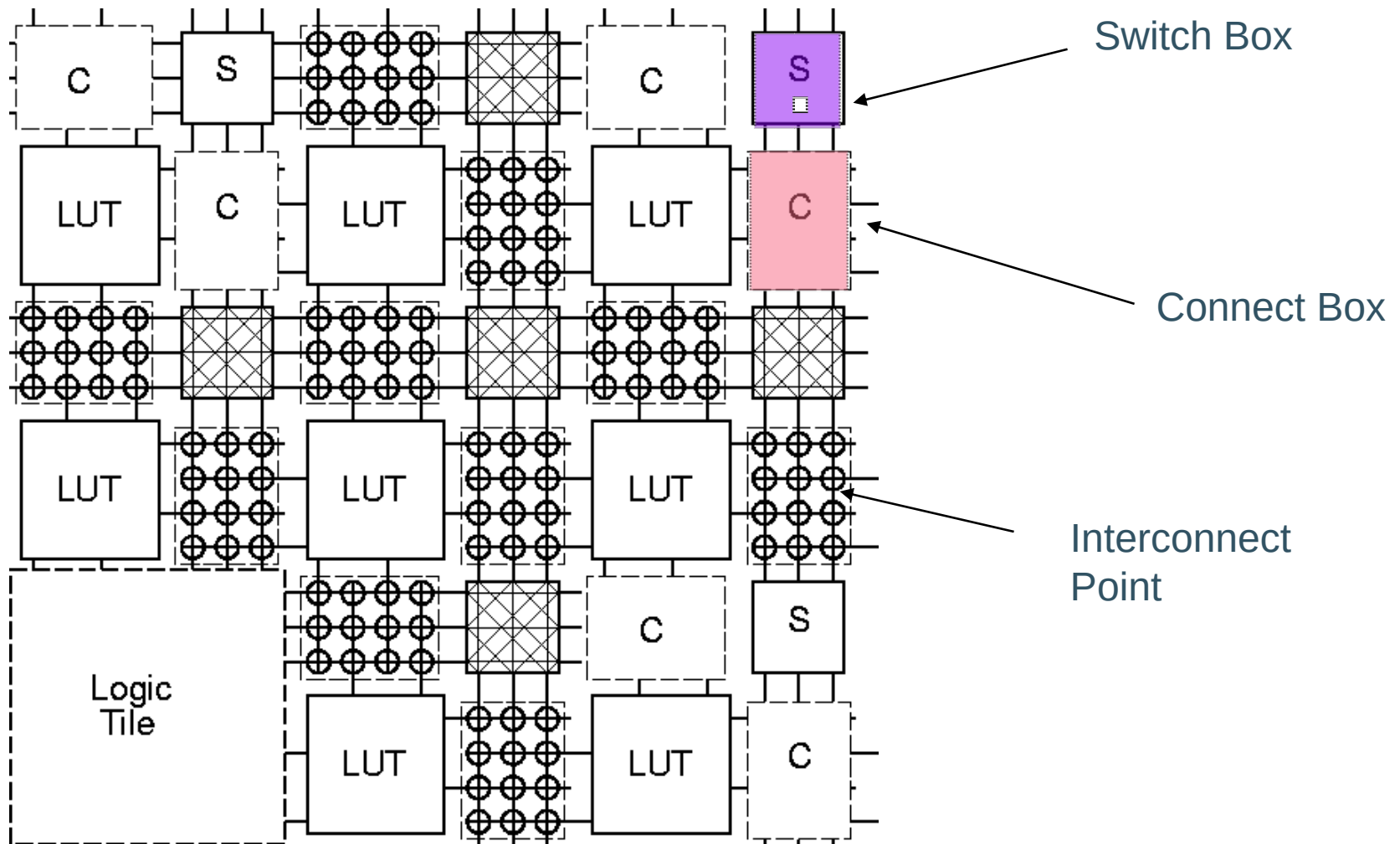


Xilinx 4000 Series

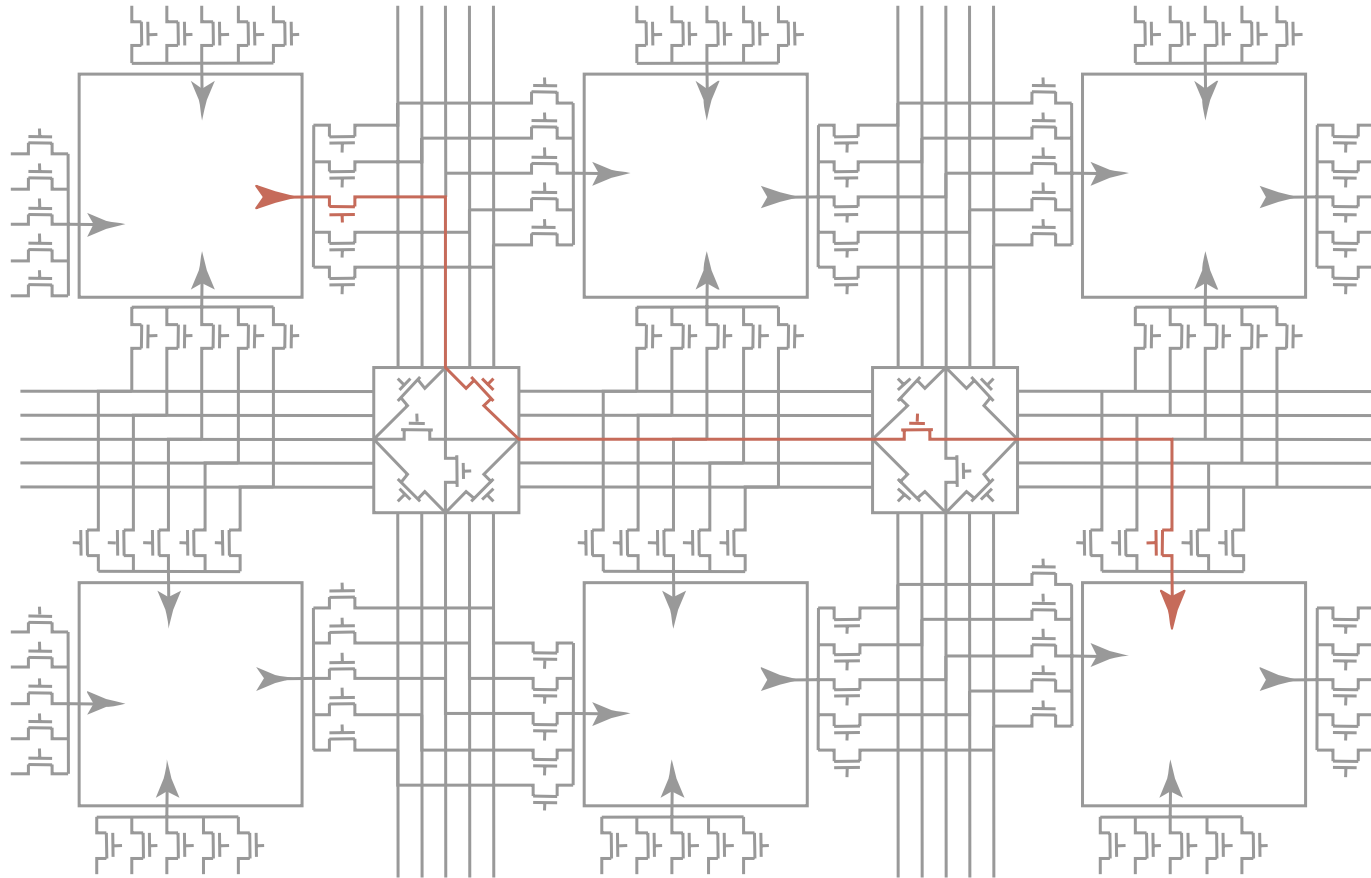
门阵列的可编程布线



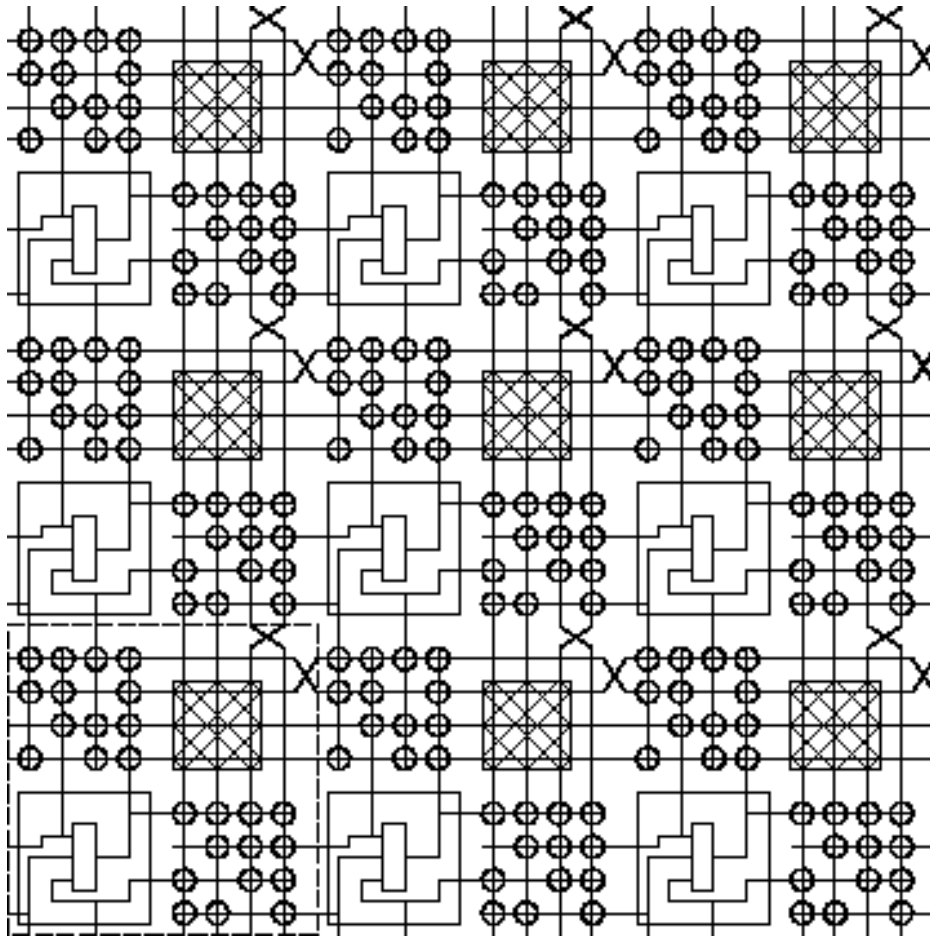
网状内联结构



网状结构内的三极管实现



网状内联的层次化结构

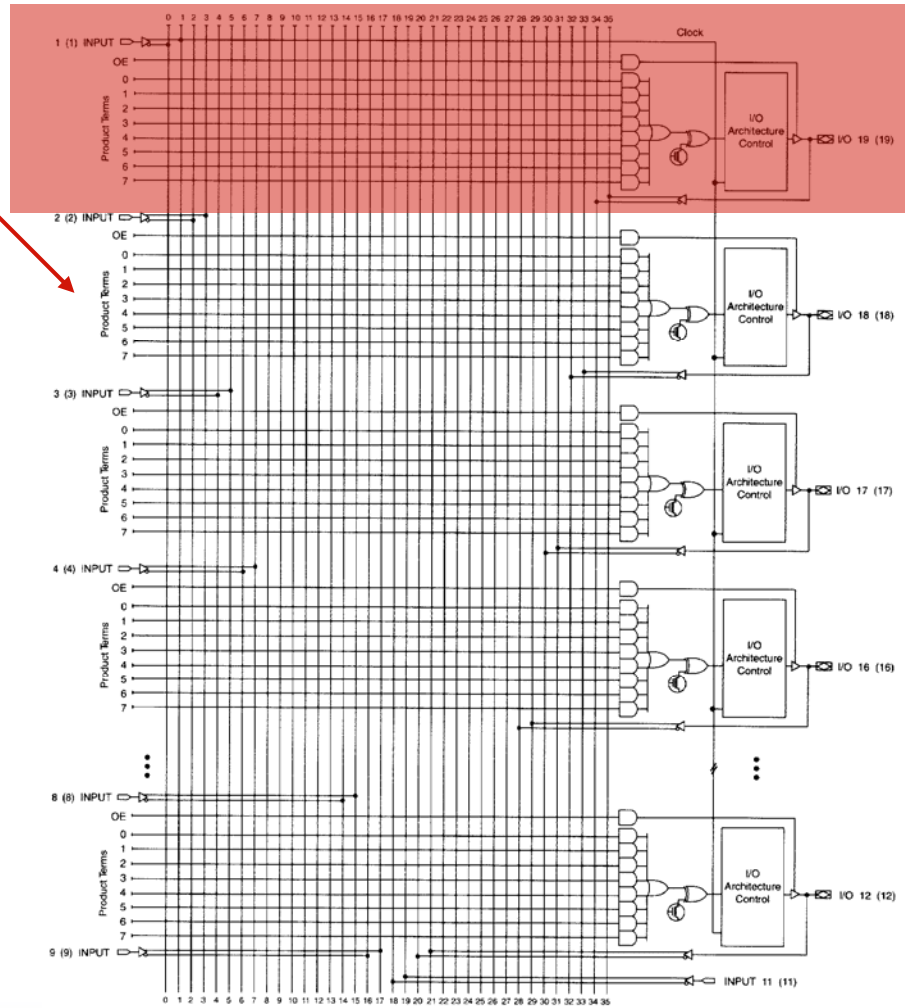


利用层叠网支持较长的连接

扇出和电阻被削减

EPLD 块示意图

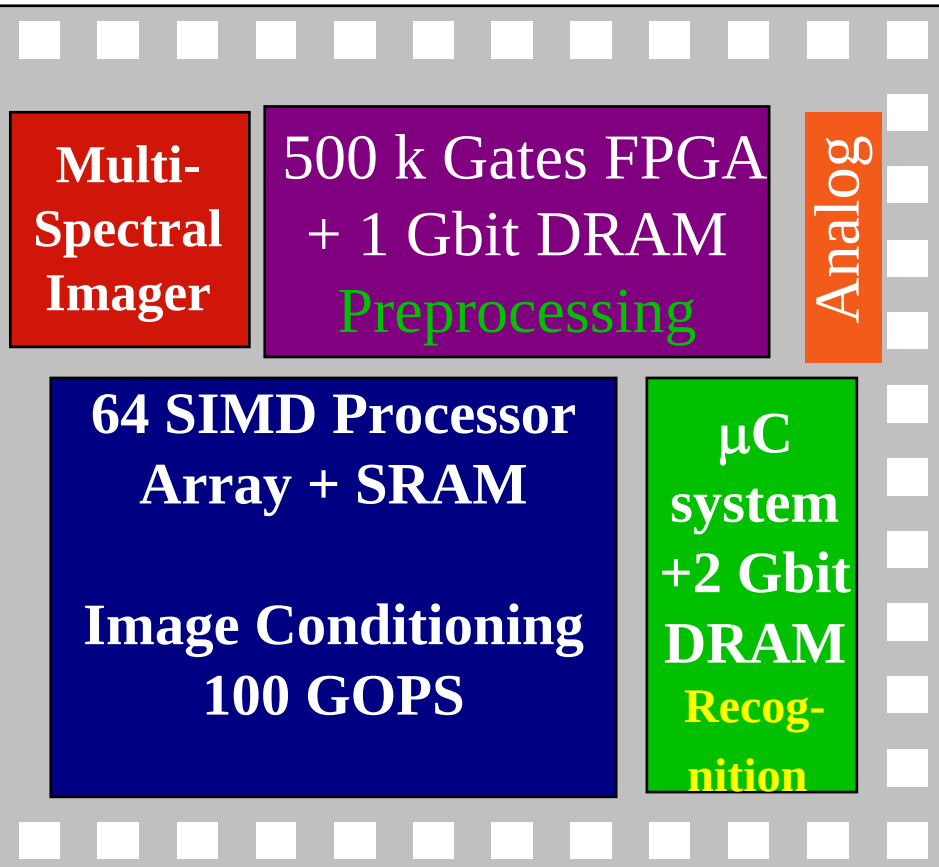
Primary inputs



宏单元

面临选择的设计：嵌入式系统

System-on-a-Chip



- ❑ 对于嵌入式应用，低成本，高性能和低功耗是最根本的目标!
- ❑ DSP 和强调控制
- ❑ 混合模式
- ❑ 结合了可编程性模块和专用性模块
- ❑ 软件主导控制